

DESCRIPTION

Title of Invention:

RESIN COMPOSITION, PREPREG, LAMINATE AND MULTILAYER PRINTED WIRING BOARD

Technical Field

[0001]

The present invention relates to a resin composition containing a polyphenylene ether derivative, and to a prepreg, a laminate and a multilayer printed wiring board.

Background Art

[0002]

Signals used in mobile communication devices, such as a cell phone, base station apparatuses for them, network infrastructure devices, such as a server and a router, large-sized computers, and the like are being increased in the speed and capacity. In accordance with this, printed wiring boards mounted on these electronic devices are required to adapt to high-frequency signals, and a substrate material having excellent dielectric characteristics (low dielectric constant and low dielectric dissipation factor; hereinafter these may be referred to as high frequency properties) in a high frequency range that enable reduction of a transmission loss is demanded. Recently, as such applications that handle high-frequency signals, practical realization and practical use planning of novel systems that handle high-frequency wireless signals in an ITS field (in connection with automobiles and traffic systems) as well as in a field of indoor short-distance communications systems, in addition to the above-mentioned electronic devices, is being promoted, and in future, low transmission-loss substrate materials are expected to be required for the printed wiring boards to be mounted on these devices.

Further, in view of the environmental problems encountered in recent years, mounting of electronic parts using a lead-free solder and achieving flame retardancy free of a halogen are demanded, and therefore the material for a printed wiring board is needed to have higher heat resistance and more excellent flame retardancy than conventional.

[0003]

Conventionally, for a printed wiring board required to have a low transmission loss, a polyphenylene ether (PPE) resin has been used as a heat-resistant thermoplastic polymer excellent in high frequency properties. For example, a method of using a polyphenylene ether and a thermosetting resin as combined has been proposed. Specifically, a resin composition containing a polyphenylene ether and an epoxy resin (see, for example, PTL 1), a resin composition using a polyphenylene ether in connection with a cyanate ester resin having a low dielectric constant among thermosetting resins (see, for example, PTL 2) and the like have been disclosed.

[0004]

However, the resin compositions described in the above-mentioned PTL's 1 and 2 are unsatisfactory collectively in the high frequency properties in a GHz region, the adhesion to conductor, the low thermal expansion coefficient, and the flame retardancy. In addition, the compatibility of polyphenylene ether with a thermosetting resin is low, and therefore the heat resistance of the resultant resin composition may often lower.

[0005]

Meanwhile, the present inventors have proposed a resin composition having a polyphenylene ether resin and a polybutadiene resin as a base, wherein the resin composition can be improved in the compatibility, heat resistance, low thermal expansion coefficient, adhesion to conductor, and the like by performing semi-IPN (semi-interpenetrating network) formation in the production stage (A-stage) of producing a resin composition containing an organic solvent (for example, PTL 3). However, the substrate material recently used for a printed wiring board is not only required to adapt to high-frequency signals, but also required to have high adhesion to conductor, low thermal expansion coefficient, high glass transition temperature, high flame retardancy, and the like due to the demands for an increase in the density, high reliability, and adaptability to consideration of the environment.

[0006]

For example, the adhesion to conductor is desired to be 0.6 kN/m or more, in terms of a copper foil peel strength as measured using a low profile copper foil (Rz: 1 to 2 μm) having a very small surface roughness on the side to be bonded to resin.

[0007]

Further, the substrate material for printed wiring board used in the application of network related devices, such as a server and a router, is needed to be stacked into the increased number of layers as the density of the wiring board is increased, and therefore the substrate material is required to have high reflow heat resistance and through-hole reliability. The glass transition temperature of the material as a yardstick for the above properties is desirably 200°C or higher, and the thermal expansion coefficient (in the Z-direction at the Tg or lower) is desirably 45 ppm/°C or less, further desirably 40 ppm/°C or less. For achieving low thermal expansion property, the incorporation of an inorganic filler into the resin composition is effective; however, in a multilayer printed wiring board with the increased number of layers, for surely obtaining the flow properties of the resin for circuit packing, the amount of the inorganic filler to be incorporated is restricted. Therefore, it is desired that even when the amount of the inorganic filler incorporated is relatively small, the resultant resin composition is desired to secure the above-mentioned required values.

[0008]

With respect to high frequency properties, excellent dielectric properties in a higher frequency range are desired, and a substrate material using an ordinary E glass substrate is desired to have a dielectric constant of 3.8 or less, more desirably 3.7 or less, and even more desirably 3.6 or less, and to have an dielectric dissipation factor of 0.007 or less, more desirably 0.006 or less. Furthermore, a substrate material generally tends to have an increased dielectric dissipation factor at a higher frequency, but is increasingly strongly needed to satisfy the above-mentioned required values in a 10 GHz or more band which is a frequency band higher than the conventional 1 to 5 GHz band for the dielectric properties values.

Citation List

Patent Literature

[0009]

PTL 1: JP 58-069046 A

PTL 2: JP 61-018937 B

PTL 3: JP 2008-95061 A

Summary of Invention

Technical Problem

[0010]

In consideration of the current situation as above, an object of the present invention is to provide a resin composition having especially excellent compatibility and having good dielectric properties in a high frequency range (low dielectric constant and low dielectric dissipation factor), high adhesion to conductor, excellent heat resistance, high glass transition temperature, low thermal expansion coefficient, and high flame retardancy, and to provide a prepreg, a laminate, and a multilayer printed wiring board using the resin composition.

Solution to Problem

[0011]

The present inventors have conducted extensive and intensive studies with a view toward solving the above-mentioned problems. As a result, the inventors have found that a prepreg and a laminate using a resin composition that contains a polyphenylene ether derivative having a specific molecular structure, a specific thermosetting resin and a styrenic thermoplastic elastomer can express excellent high frequency properties, high heat resistance, high adhesion to conductors, high glass transition temperature, low thermal expansion coefficient and high flame retardancy, and have completed the present invention.

That is, the present invention relates to the following [1] to [16].

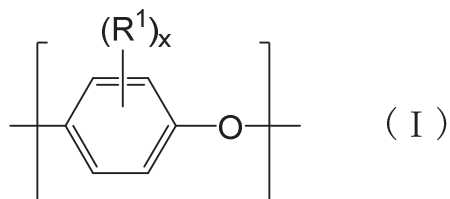
[0012]

[1] A resin composition containing:

(A) a polyphenylene ether derivative having an N-substituted maleimide structure-containing group and a structural unit represented by the following general formula (I) in one molecule,

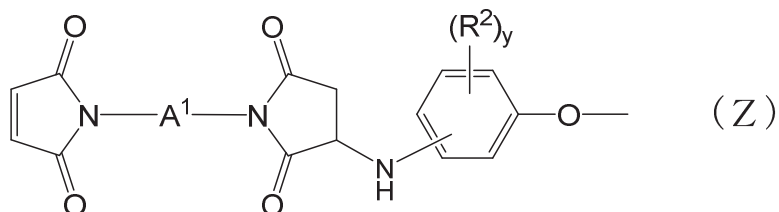
(B) at least one thermosetting resin selected from the group consisting of an epoxy resin, a cyanate resin and a maleimide compound, and

(C) a styrenic thermoplastic elastomer:

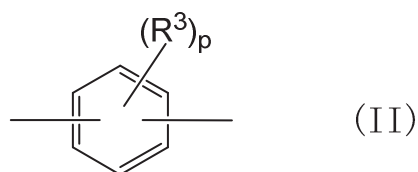


wherein R^1 each independently represents an aliphatic hydrocarbon group having 1 to 5 carbon atoms, or a halogen atom, and x represents an integer of 0 to 4.

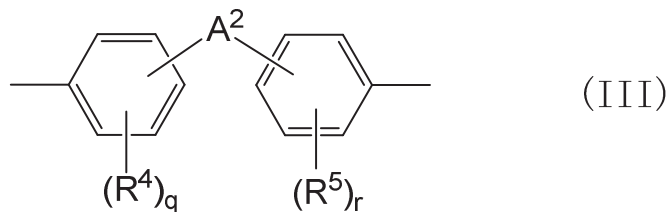
[2] The resin composition according to the above [1], wherein the N-substituted maleimide structure-containing group is a group represented by the following general formula (Z):



wherein R^2 each independently represents an aliphatic hydrocarbon group having 1 to 5 carbon atoms, or a halogen atom, y represents an integer of 0 to 4, and A^1 represents a group represented by the following general formula (II), (III), (IV) or (V):

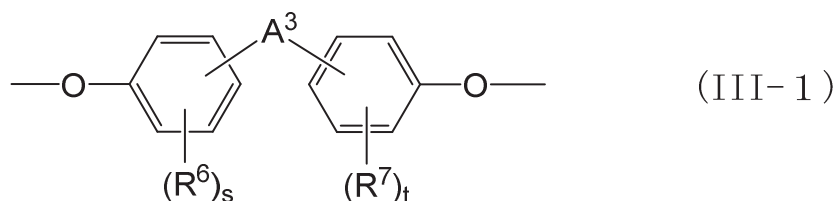


wherein R^3 each independently represents an aliphatic hydrocarbon group having 1 to 5 carbon atoms, or a halogen atom, p represents an integer of 0 to 4:

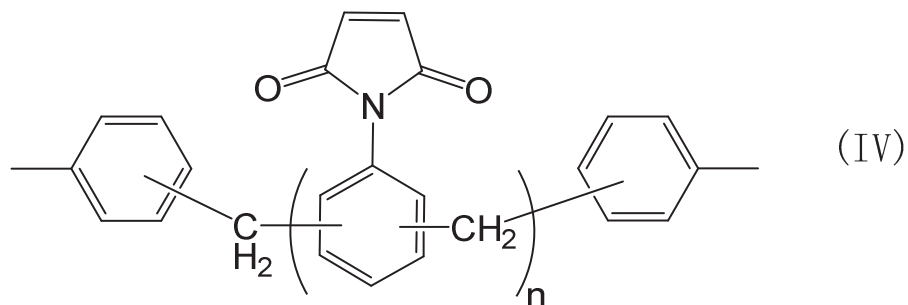


wherein R^4 and R^5 each independently represent an aliphatic hydrocarbon group having 1 to 5 carbon atoms, or a halogen atom, A^2 represents an alkylene group having 1 to 5 carbon atoms, an alkylidene group having 2 to 5 carbon atoms, an ether group, a sulfide group, a sulfonyl group, a carbonyloxy group, a keto

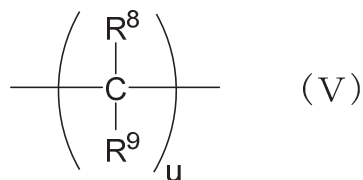
group, a single bond, or a group represented by the following general formula (III-1), and q and r each independently represent an integer of 0 to 4:



wherein R⁶ and R⁷ each independently represent an aliphatic hydrocarbon group having 1 to 5 carbon atoms, or a halogen atom, A³ represents an alkylene group having 1 to 5 carbon atoms, an isopropylidene group, an ether group, a sulfide group, a sulfonyl group, a carbonyloxy group, a keto group or a single bond, and s and t each independently represent an integer of 0 to 4:

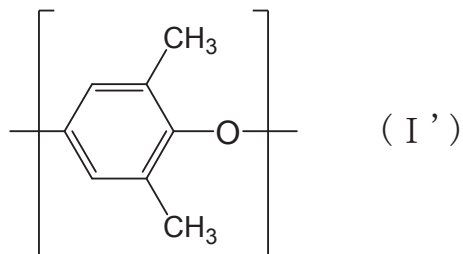


wherein n represents an integer of 0 to 10:

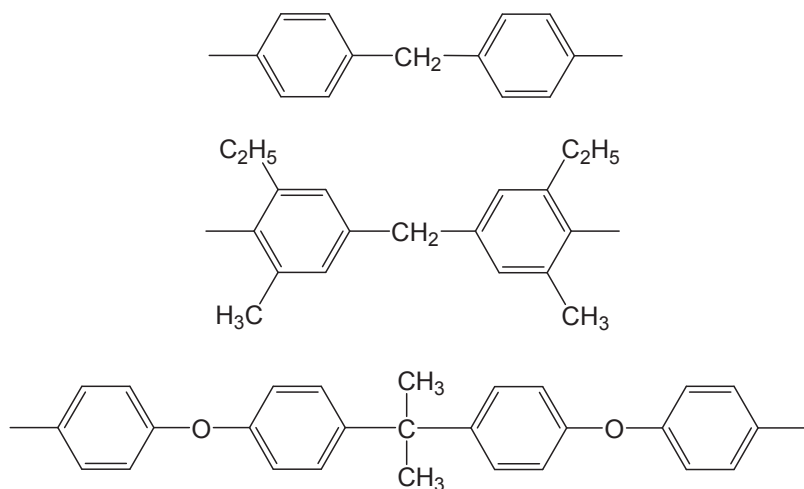


wherein R⁸ and R⁹ each independently represent a hydrogen atom, or an aliphatic hydrocarbon group having 1 to 5 carbon atoms, and u represents an integer of 1 to 8.

[3] The resin composition according to the above [1] or [2], wherein the structural unit represented by the general formula (I) is a structural unit represented by the following formula (I'):

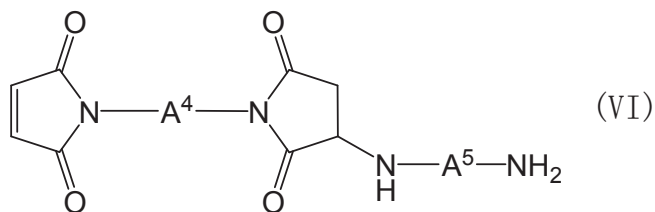


[4] The resin composition according to the above [2] or [3], wherein A¹ in the general formula (Z) is a group represented by any of the following formulae:

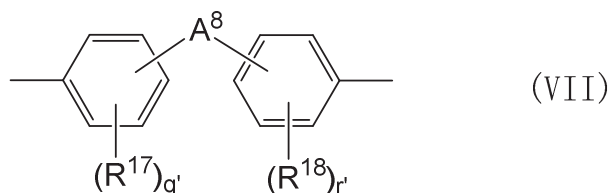


[5] The resin composition according to any one of the above [1] to [4], wherein the number average molecular weight of the component (A) is from 5,000 to 12,000.

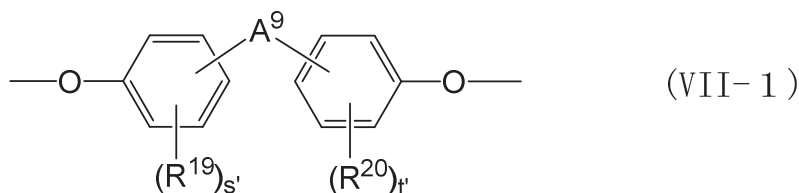
[6] The resin composition according to any one of the above [1] to [5], wherein the maleimide compound as the component (B) is a polymaleimide compound (a) having at least two N-substituted maleimide groups in one molecule, or a polyaminobismaleimide compound (c) represented by the following general formula (VI):



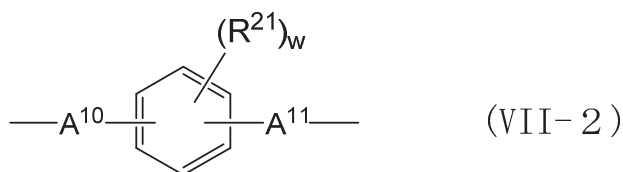
wherein A⁴ has the same definition as that of A¹ in the general formula (Z), A⁵ represents a group represented by the following general formula (VII):



wherein R^{17} and R^{18} each independently represent an aliphatic hydrocarbon group having 1 to 5 carbon atoms, an alkoxy group having 1 to 5 carbon atoms, a hydroxyl group or a halogen atom, A^8 represents an alkylene group having 1 to 5 carbon atoms, an alkylidene group having 2 to 5 carbon atoms, an ether group, a sulfide group, a sulfonyl group, a carbonyloxy group, a keto group, a fluorenylene group, a single bond, or a group represented by the following general formula (VII-1) or (VII-2), and q' and r' each independently represent an integer of 0 to 4:



wherein R^{19} and R^{20} each independently represent an aliphatic hydrocarbon group having 1 to 5 carbon atoms, or a halogen atom, A^9 represents an alkylene group having 1 to 5 carbon atoms, an isopropylidene group, an m-phenylenediisopropylidene group, a p-phenylenediisopropylidene group, an ether group, a sulfide group, a sulfonyl group, a carbonyloxy group, a keto group or a single bond, and s' and t' each independently represent an integer of 0 to 4:



wherein R^{21} represents an aliphatic hydrocarbon group having 1 to 5 carbon atoms, or a halogen atom, A^{10} and A^{11} each independently represent an alkylene group having 1 to 5 carbon atoms, an isopropylidene group, an ether group, a sulfide group, a sulfonyl group, a carbonyloxy group, a keto group, or a single bond, and w represents an integer of 0 to 4.

[7] The resin composition according to any one of the above [1] to [6], wherein the content ratio of the component (A) to the component (B) $[(A)/(B)]$ is from 5/95 to 80/20 by mass.

[8] The resin composition according to any one of the above [1] to [7], wherein the component (C) is at least one selected from a styrene-butadiene-styrene block copolymer hydrogenate (SEBS, SBBS), a styrene-isoprene-styrene block copolymer hydrogenate (SEPS) and a styrene-maleic anhydride copolymer (SMA).

[9] The resin composition according to any one of the above [1] to [8], wherein the content ratio of the component (C) is from 5 to 60 parts by mass relative to 100 parts by mass of the sum total of the components (A) to (C).

[10] The resin composition according to any one of the above [1] to [9], further containing an inorganic filler (D).

[11] The resin composition according to any one of the above [1] to [10], further containing a curing accelerator (E).

[12] The resin composition according to any one of the above [1] to [11], further containing a flame retardant (F).

[13] The resin composition according to any one of the above [1] to [12], further containing an organic solvent.

[14] A prepreg including the resin composition of any one of the above [1] to [13] and a sheet-form fiber reinforced substrate.

[15] A laminate including the prepreg of the above [14] and a metal foil.

[16] A multilayer printed wiring board including the prepreg of the above [14] or the laminate of the above [15].

Advantageous Effects of Invention

[0013]

The resin composition of the present invention has particularly good compatibility, excellent high frequency properties (low dielectric constant, low dielectric dissipation factor), high adhesion to conductor, excellent heat resistance, high glass transition temperature, low thermal expansion coefficient and high flame retardancy. Accordingly, the prepreg and the laminate to be obtained using the resin composition can be favorably used for electronic parts such as multilayer printed wiring boards, etc.

Description of Embodiments

[0014]

Embodiments of the present invention are described in detail hereinafter.

[0015]

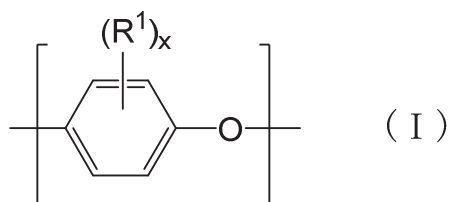
[Resin Composition]

One aspect of the present invention is a resin composition containing:

(A) a polyphenylene ether derivative having an N-substituted maleimide structure-containing group and a structural unit represented by the following general formula (I) in one molecule [hereinafter this may be simply abbreviated as polyphenylene ether derivative (A) or component (A)],

(B) at least one thermosetting resin selected from the group consisting of an epoxy resin, a cyanate resin and a maleimide compound [hereinafter this may be simply abbreviated as thermosetting resin (B) or component (B)], and

(C) a styrenic thermoplastic elastomer [hereinafter this may be abbreviated as component (C)].



wherein R¹ each independently represents an aliphatic hydrocarbon group having 1 to 5 carbon atoms, or a halogen atom, x represents an integer of 0 to 4.

The components are described in order.

[0016]

(Polyphenylene Ether Derivative (A))

The polyphenylene ether derivative (A) has an N-substituted maleimide structure-containing group and a structural unit represented by the above-mentioned general formula (I) in one molecule. In particular, since the polyphenylene ether derivative (A) has at least one N-substituted maleimide structure-containing group in one molecule, the resin composition can have excellent high frequency properties (low dielectric constant, low dielectric dissipation factor), high adhesion to conductor, excellent heat resistance, high glass transition temperature, low thermal expansion coefficient and high flame retardancy. Here, the thermal expansion coefficient as referred to in the present invention means a value also called a linear expansion coefficient.

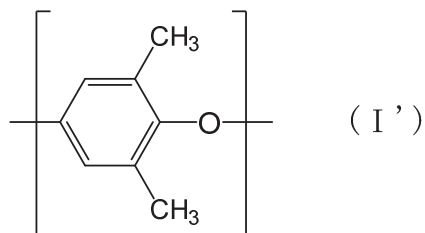
R¹ in the general formula (I) each independently represents an aliphatic hydrocarbon group having 1 to 5 carbon atoms, or a halogen atom. Examples of the aliphatic hydrocarbon group include a methyl group, an ethyl group, an n-propyl group, an isopropyl group, an n-butyl group, an isobutyl group, a t-butyl

group, an n-pentyl group, etc. The aliphatic hydrocarbon group may be an aliphatic hydrocarbon group having 1 to 3 carbon atoms, and may be a methyl group. Examples of the halogen atom include a fluorine atom, a chlorine atom, a bromine atom, an iodine atom, etc.

Among the above, R^1 may be an aliphatic hydrocarbon group having 1 to 5 carbon atoms.

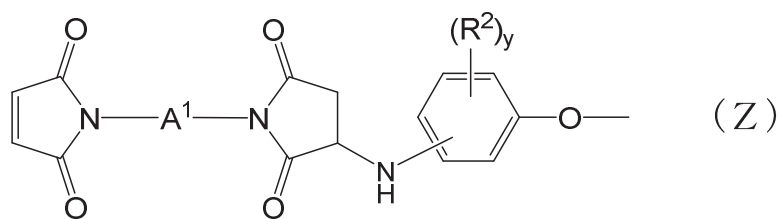
x is an integer of 0 to 4, and may be an integer of 0 to 2, and may 2. When x is 1 or 2, R^1 may be substituted at the ortho-position on the benzene ring (based on the substitution position of the oxygen atom). When x is 2 or more, plural R^1 's may be the same or different.

Specifically, the structural unit represented by the general formula (I) may be a structural formula represented by the following general formula (I').



[0017]

The N-substituted maleimide structure-containing group that the polyphenylene ether derivative (A) has may be, from the viewpoint of high frequency properties (low dielectric constant, low dielectric dissipation factor), adhesion to conductor, heat resistance, glass transition temperature, thermal expansion coefficient and flame retardancy, a group containing a bismaleimide structure in which the nitrogen atoms of the two maleimide groups bond to each other via an organic group, and may be a group represented by the following general formula (Z).



wherein R^2 each independently represents an aliphatic hydrocarbon group having 1 to 5 carbon atoms, or a halogen atom, y represents an integer of 0 to 4, A^1 represents a group represented by the following general formula (II), (III), (IV) or (V).

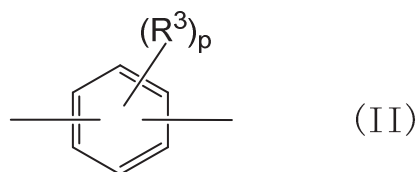
[0018]

The aliphatic hydrocarbon group having 1 to 5 carbon atoms and the halogen atom that R^2 represents may be described in the same manner as that for the case of R^1 .

y is an integer of 0 to 4, and may be an integer of 0 to 2, and may be 0. When y is an integer of 2 or more, plural R^2 's may be the same or different.

The group represented by the general formula (II), (III), (IV) or (V) that A^1 represents is as follows.

[0019]

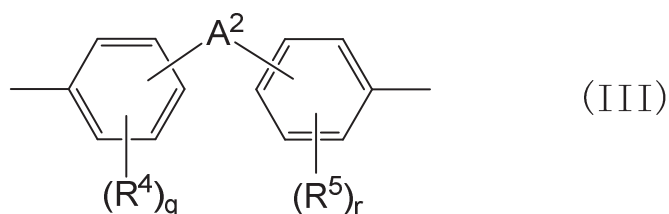


wherein R^3 each independently represents an aliphatic hydrocarbon group having 1 to 5 carbon atoms, or a halogen atom, p represents an integer of 0 to 4.

The aliphatic hydrocarbon group having 1 to 5 carbon atoms and the halogen atom that R^3 represents may be described in the same manner as that for the case of R^1 .

p is an integer of 0 to 4, and, from the viewpoint of easy availability, may be an integer of 0 to 2, or 0 or 1, or 0. When p is an integer of 2 or more, plural R^3 's may be the same or different.

[0020]



wherein R^4 and R^5 each independently represent an aliphatic hydrocarbon group having 1 to 5 carbon atoms, or a halogen atom, A^2 represents an alkylene group having 1 to 5 carbon atoms, an alkylidene group having 2 to 5 carbon atoms, an ether group, a sulfide group, a sulfonyl group, a carbonyloxy group, a keto group, a single bond, or a group represented by the following general formula (III-1), q and r each independently represent an integer of 0 to 4.

The aliphatic hydrocarbon group having 1 to 5 carbon atoms and the halogen atom that R^4 and R^5 represent include the same ones as those for R^1 .

The aliphatic hydrocarbon group may be an aliphatic hydrocarbon group having 1 to 3 carbon atoms, and may be a methyl group or an ethyl group, and may be an ethyl group.

Examples of the alkylene group having 1 to 5 carbon atoms that A^2 represents include a methylene group, a 1,2-dimethylene group, a 1,3-trimethylene group, a 1,4-tetramethylene group, a 1,5-pentamethylene group, etc. The alkylene group may be, from the viewpoint of high frequency properties (low dielectric constant, low dielectric dissipation factor), adhesion to conductor, heat resistance, glass transition temperature, thermal expansion coefficient and flame retardancy, an alkylene group having 1 to 3 carbon atoms, or may be a methylene group.

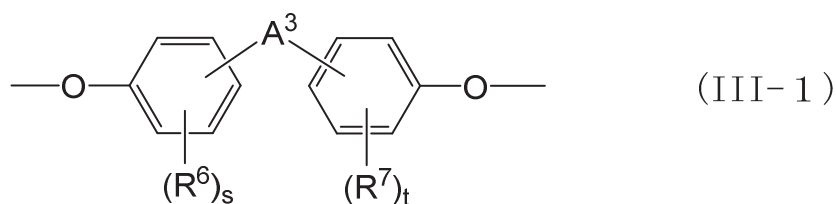
Examples of the alkylidene group having 2 to 5 carbon atoms that A^2 represents include an ethylidene group, a propylidene group, an isopropylidene group, a butylidene group, an isobutylidene group, a pentylidene group, an isopentylidene group, etc. Among these, from the viewpoint of high frequency properties (low dielectric constant, low dielectric dissipation factor), adhesion to conductor, heat resistance, glass transition temperature, thermal expansion coefficient and flame retardancy, it may be an isopropylidene group.

Among the above-mentioned choices, A^2 may be an alkylene group having 1 to 5 carbon atoms or an alkylidene group having 2 to 5 carbon atoms.

q and r each are independently an integer of 0 to 4, and, from the viewpoint of easy availability, may be an integer of 0 to 2, or 0 or 2. When q or r is an integer of 2 or more, plural R^4 's or plural R^5 's each may be the same or different.

The group represented by the general formula (III-1) that A^2 represents is as follows.

[0021]



wherein R^6 and R^7 each independently represent an aliphatic hydrocarbon group having 1 to 5 carbon atoms, or a halogen atom, A^3 represents an alkylene group having 1 to 5 carbon atoms, an isopropylidene group, an ether group, a sulfide

group, a sulfonyl group, a carbonyloxy group, a keto group or a single bond, s and t each independently represent an integer of 0 to 4.

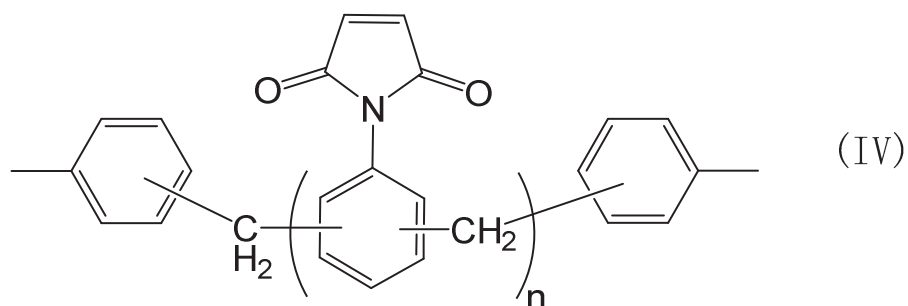
The aliphatic hydrocarbon group having 1 to 5 carbon atoms and the halogen atom that R^6 and R^7 represent may be described in the same manner as that for the case of R^4 and R^5 .

The alkylene group having 1 to 5 carbon atoms and the alkylidene group having 2 to 5 carbon atoms that A^3 represents include the same ones as the alkylene group having 1 to 5 carbon atoms and the alkylidene group having 2 to 5 carbon atoms that A^2 represents.

From among the above-mentioned choices, the alkylidene group having 2 to 5 carbon atoms may be selected for A^3 .

s and t each are independently an integer of 0 to 4, and, from the viewpoint of easy availability, may be an integer of 0 to 2, or may be 0 or 1, or may be 0. When s or t is an integer of 2 or more, plural R^6 's or plural R^7 's each may be the same or different.

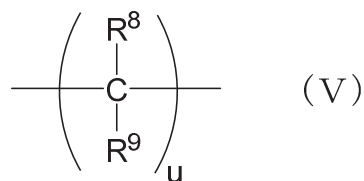
[0022]



wherein n represents an integer of 0 to 10.

From the viewpoint of easy availability, n may be an integer of 0 to 5, or may be an integer of 0 to 3.

[0023]



wherein R^8 and R^9 each independently represent a hydrogen atom, or an aliphatic hydrocarbon group having 1 to 5 carbon atoms, u represents an integer of 1 to 8.

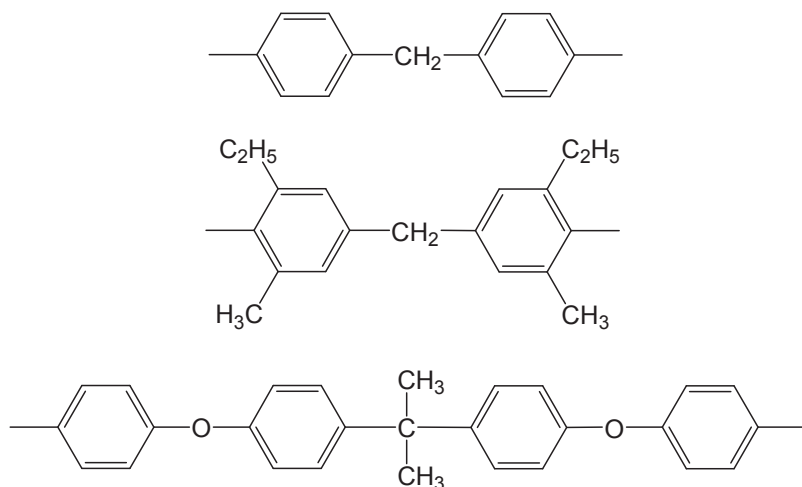
The aliphatic hydrocarbon group having 1 to 5 carbon atoms and the halogen atom that R^8 and R^9 represent may be described in the same manner as

that for the case of R¹.

u is an integer of 1 to 8, and may be an integer of 1 to 3, or may be 1.

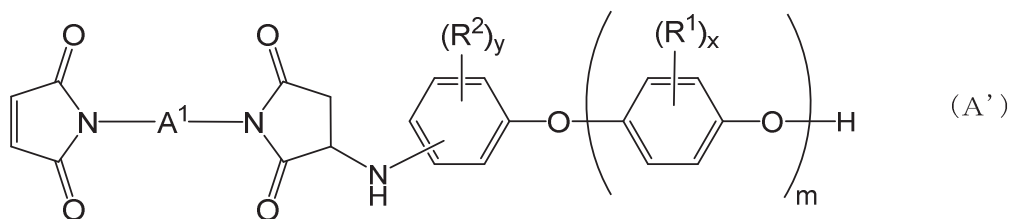
[0024]

A¹ in the group represented by the general formula (Z) may be, from the viewpoint of high frequency properties (low dielectric constant, low dielectric dissipation factor), adhesion to conductor, heat resistance, glass transition temperature, thermal expansion coefficient and flame retardancy, a group represented by any of the following formulae.



[0025]

The polyphenylene ether derivative (A) may be a polyphenylene ether derivative represented by the following general formula (A').

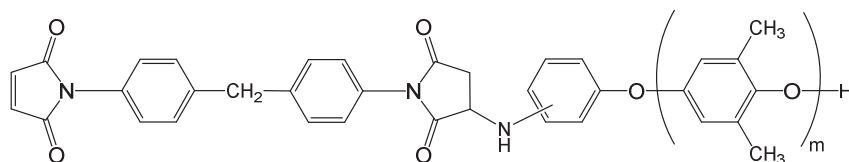


wherein A¹, R¹, R², x and y are as defined hereinabove, m represents an integer of 1 or more.

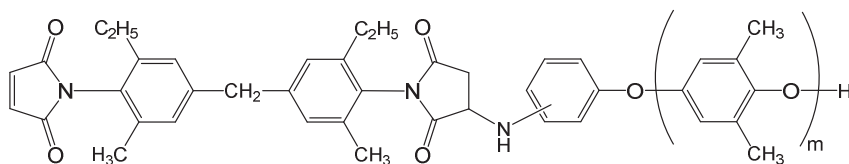
m may be an integer of 1 to 300, or may be an integer of 10 to 300, or may be an integer of 30 to 200, or may be an integer of 50 to 150.

[0026]

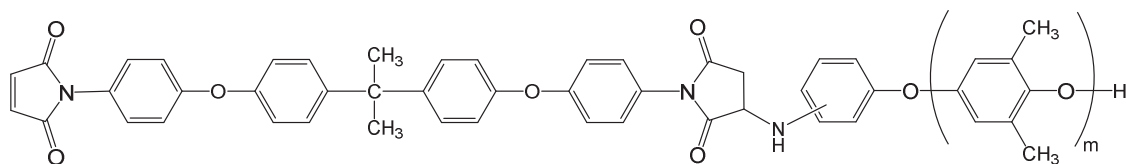
The polyphenylene ether derivative (A) may be a polyphenylene ether derivative represented by any of the following formulae.



(A' - 1)



(A' - 2)



(A' - 3)

wherein m is the same as m in the general formula (A').

[0027]

From the viewpoint of inexpensive raw materials, the derivative may be a polyphenylene ether derivative of the above formula (A'-1), from the viewpoint of excellent dielectric properties and low water absorbability, it may be a polyphenylene ether derivative represented by the formula (A'-2), and from the viewpoint of excellent adhesion to conductor and mechanical properties (elongation, strength at break, etc.), it may be a polyphenylene ether derivative represented by the formula (A'-3). Accordingly, in conformity to the intended properties, one alone or two or more of the polyphenylene ether derivatives of the formulae (A'-1) to (A'-3) may be used either singly or as combined.

[0028]

The number average molecular weight of the polyphenylene ether derivative (A) of the present invention may be 5,000 to 12,000, or may be 7,000 to 12,000, or may be 7,000 to 10,000. When the number average molecular weight is 5,000 or more, the resin composition of the present invention and the prepreg and the laminate using the composition tend to have a more favorable glass transition temperature. When the number average molecular weight is 12,000 or less, the resin composition of the present invention tend to be readily molded

into a laminate with better formability.

In this description, the number average molecular weight is a value calculated based on the calibration curve drawn using a standard polystyrene, according to gel permeation chromatography (GPC), and more precisely, a value measured according to the number average molecular weight measurement method described in the section of Examples.

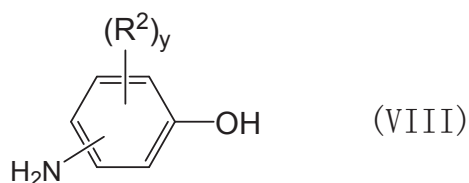
[0029]

(Method for Producing Polyphenylene Ether Derivative (A))

The polyphenylene ether derivative (A) may be obtained, for example, according to the production method mentioned below.

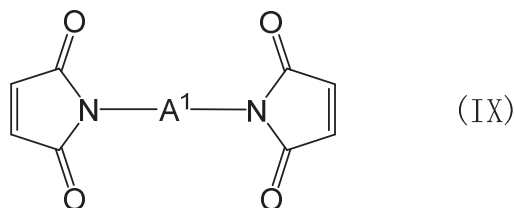
First, an aminophenol compound represented by the following general formula (VIII) [hereinafter referred to as aminophenol compound (VIII)] is reacted with a polyphenylene ether having, for example, a number average molecular weight of 15,000 to 25,000 in an organic solvent in a mode of known redistribution reaction, as associated with reduction in the polyphenylene ether, to thereby produce a polyphenylene ether compound having a primary amino group in one molecule (A'') (hereinafter this may be simply referred to as polyphenylene ether compound (A'')), and then the polyphenylene ether compound (A'') is reacted with a bismaleimide compound represented by the general formula (IX) [hereinafter referred to as bismaleimide compound (IX)] in a mode of Michael addition reaction to produce the polyphenylene ether derivative (A).

[0030]



wherein R^2 and y are the same as those in the general formula (I).

[0031]



wherein A^1 is the same as in the general formula (I).

[0032]

Examples of the aminophenol compound (VIII) include o-aminophenol, m-aminophenol, p-aminophenol, etc. Among these, from the viewpoint of the reaction yield in producing the polyphenylene ether compound (A"), as well as the heat resistance in producing resin composition, prepreg and laminate, the compound may be m-aminophenol or p-aminophenol, or may be p-aminophenol.

[0033]

The molecular weight of the polyphenylene ether compound (A") may be controlled by the amount to be used of the aminophenol compound (VIII), and when the amount of the aminophenol compound (VIII) used is larger, the molecular weight of the polyphenylene ether compound (A") is lower. Namely, the amount to be used of the aminophenol compound (VIII) may be adequately controlled so that the number average molecular weight of the polyphenylene ether derivative (A) to be produced finally could fall within a preferred range.

The amount to be incorporated of the aminophenol compound (VIII) is not specifically limited, but for example, when the number average molecular weight of the polyphenylene ether to be reacted with the aminophenol compound (VIII) is 15,000 to 25,000, the amount may fall within a range of 0.5 to 6 parts by mass relative to 100 parts by mass of the polyphenylene ether to give a polyphenylene ether derivative (A) having a number average molecular weight of 5,000 to 12,000.

[0034]

Examples of the organic solvent for use in the production step for the polyphenylene ether compound (A") include, though not specifically limited thereto, alcohols such as methanol, ethanol, butanol, butyl cellosolve, ethylene glycol monomethyl ether, propylene glycol monomethyl ether, etc.; ketones such as acetone, methyl ethyl ketone, methyl isobutyl ketone, cyclohexanone, etc.; aromatic hydrocarbons such as toluene, xylene, mesitylene, etc.; esters such as methoxyethyl acetate, ethoxyethyl acetate, butoxyethyl acetate, ethyl acetate, etc.; nitrogen-containing compounds such as N,N-dimethylformamide, N,N-dimethylacetamide, N-methyl-2-pyrrolidone, etc. One alone or two or more kinds of these may be used either singly or as combined. Among these, from the viewpoint of solubility, toluene, xylene and mesitylene may be selected.

[0035]

In the production step for the polyphenylene ether compound (A"), a reaction catalyst may be used as needed. To the reaction catalyst, for example, the reaction catalyst in redistribution reaction is applicable. For example, from

the viewpoint of producing the polyphenylene ether compound (A'') having a stable number average molecular weight with good reproducibility, an organic peroxide such as t-butylperoxyisopropyl monocarbonate or the like and a metal carboxylate such as manganese naphthenate or the like may be used as combined. The amount of the reaction catalyst to be used is not specifically limited. From the viewpoint of the reaction speed and antigelation in producing the polyphenylene ether compound (A''), for example, the amount of the organic peroxide may be 0.5 to 5 parts by mass and that of the metal carboxylate may be 0.05 to 0.5 parts by mass relative to 100 parts by mass of the polyphenylene ether to be reacted with the aminophenol compound (VIII).

[0036]

The aminophenol compound (VIII), the polyphenylene ether having a number average molecular weight of 15,000 to 25,000, an organic solvent and optionally a reaction catalyst are put in a reactor each in a predetermined amount, and reacted with heating, keeping the heat and stirring to give the polyphenylene ether compound (A''). For the reaction temperature and the reaction time in this step, the reaction conditions in known redistribution reaction are applicable.

From the viewpoint of operability and antigelation, and from the viewpoint of controlling the molecular weight of the polyphenylene ether compound (A'') for obtaining the component (A) having a desired number average molecular weight, for example, the reaction may be carried out at a reaction temperature of 70 to 110°C and for a reaction time of 1 to 8 hours.

[0037]

A solution of the polyphenylene ether compound (A'') thus produced in the manner as above may be continuously and directly fed to the next step of producing the polyphenylene ether derivative (A). In this stage, the solution of the polyphenylene ether compound (A'') may be cooled, or may be controlled to be at the reaction temperature in the next step. As needed, the solution may be concentrated to remove a part of the organic solvent, or may be diluted by adding an organic solvent thereto, as described below.

[0038]

Examples of the bismaleimide compound (IX) to be used in producing the polyphenylene ether derivative (A) include bis(4-maleimidophenyl)methane, polyphenylmethanemaleimide, bis(4-maleimidophenyl) ether, bis(4-maleimidophenyl) sulfone,

3,3'-dimethyl-5,5'-diethyl-4,4'-diphenylmethanebismaleimide,
 4-methyl-1,3-phenylenebismaleimide, m-phenylenebismaleimide,
 2,2-bis(4-(4-maleimidophenoxy)phenyl)propane, bis(4-maleimidophenyl) sulfone,
 bis(4-maleimidophenyl) sulfide, bis(4-maleimidophenyl) ketone,
 2,2-bis(4-(4-maleimidophenoxy)phenyl)propane,
 bis(4-(4-maleimidophenoxy)phenyl) sulfone,
 4,4'-bis(3-maleimidophenoxy)biphenyl, and
 1,6-bismaleimido-(2,2,4-trimethyl)hexane. These may be used individually or in
 combination.

Of these, bis(4-maleimidophenyl)methane,
 3,3'-dimethyl-5,5'-diethyl-4,4'-diphenylmethanebismaleimide, and
 2,2-bis(4-(4-maleimidophenoxy)phenyl)propane may be selected.

Bis(4-maleimidophenyl)methane may be used because the polyphenylene
 ether derivative containing the formula (A'-1) above is obtained and it is
 inexpensive. 3,3'-Dimethyl-5,5'-diethyl-4,4'-diphenylmethanebismaleimide may
 be used because the polyphenylene ether derivative containing the formula (A'-2)
 above is obtained and exhibits excellent dielectric properties and low water
 absorption properties. 2,2-Bis(4-(4-maleimidophenoxy)phenyl)propane may be
 used because the polyphenylene ether derivative containing the formula (A'-3)
 above is obtained and exhibits high adhesion to conductor and excellent
 mechanical properties (elongation, strength at break).

[0039]

The amount of the bismaleimide compound (IX) is determined according to
 the amount of the aminophenol compound (VIII) used. Specifically, the
 bismaleimide compound may be incorporated so that the equivalent ratio
 (Tb1/Ta1) of the maleimide group equivalent (Tb1) of the bismaleimide compound
 (IX) to the -NH_2 group equivalent (Ta1) of the aminophenol compound (VIII) could
 be in the range of 2 to 6, or in a range of 2 to 4. When the bismaleimide compound
 is used in the equivalent ratio range as above, the resin composition, the prepreg
 and the laminate of the present invention tend to have more excellent heat
 resistance, high glass transition temperature and high flame retardancy.

[0040]

In the Michael addition reaction conducted when producing the
 polyphenylene ether derivative (A), a reaction catalyst may be used as needed.
 With respect to the reaction catalyst used, there is no particular limitation.

However, examples of the reaction catalyst include acidic catalysts, such as p-toluenesulfonic acid; amines, such as triethylamine, pyridine, and tributylamine; imidazole compounds, such as methylimidazole and phenylimidazole; and phosphorus catalysts, such as triphenylphosphine. These may be used individually or in combination. With respect to the amount of the reaction catalyst incorporated, there is no particular limitation. However, for example, relative to 100 parts by mass of the polyphenylene ether compound (A"), the reaction catalyst can be used in an amount in the range of 0.01 to 5 parts by mass.

[0041]

The bismaleimide compound (IX) and optionally a reaction catalyst and others are put into the solution of the polyphenylene ether compound (A") solution each in a predetermined amount, and reacted with heating, keeping the heat and stirring in a mode of Michael reaction to give the polyphenylene ether derivative (A). Regarding the reaction conditions in this step, for example, from the viewpoint of operability and antigelation, the reaction temperature may be 50 to 160°C, and the reaction time may be 1 to 10 hours. In addition, in this step, an organic solvent may be added, or the reaction system may be concentrated as mentioned above, to thereby control the reaction concentration (solid concentration, and the solution viscosity. For the additional organic solvent, the organic solvents exemplified in the section of the production step for the polyphenylene ether compound (A") are applicable, and one alone or two or more kinds of these may be used either singly or as combined. Among these, from the viewpoint of solubility, methyl ethyl ketone, cyclohexanone, propylene glycol monomethyl ether, N,N-dimethylformamide and N,N-dimethylacetamide may be selected.

[0042]

The reaction concentration (solid concentration) in the production step for the polyphenylene ether derivative (A) and the polyphenylene ether (A") is not specifically limited, but, for example, in each production step, the concentration may be 10 to 60% by mass, and may be 20 to 50% by mass. When the reaction concentration is 10% by mass or more, the reaction speed is not too low, and tends to be favorable from the viewpoint of production cost. When the reaction concentration is 60% by mass or less, better solubility tends to be attained. If so, in addition, the solution viscosity may be low and the stirring efficiency tends to

be good to suppress gelation.

After production of the polyphenylene ether derivative (A), a part or all of the organic solvent may be optionally removed from the solution for concentration, or an additional organic solvent may be added thereto for dilution, in accordance with the operability in taking out the derivative from the reactor or with the use condition (for example, solution viscosity or solution concentration suitable for production of prepreg) in preparing the resin composition of the present invention by adding various thermosetting resins to the polyphenylene ether derivative (A). The additional organic solvent is not specifically limited, and one or more organic solvents mentioned above may be used.

[0043]

The formation of the polyphenylene ether compound (A") and the polyphenylene ether derivative (A) in the above-mentioned production steps may be confirmed through GPC and IR analysis by sampling a small amount of the product after each step.

First, with respect to the polyphenylene ether compound (A"), the production of a desired polyphenylene ether compound (A") can be confirmed by GPC showing that the molecular weight is reduced to be lower than the polyphenylene ether having a number average molecular weight of 15,000 to 25,000 and that the peak of the aminophenol compound (VIII) as a raw material has disappeared, and by IR analysis showing that a peak of the primary amino group appears at 3,300 to 3,500 cm^{-1} . With respect to the polyphenylene ether derivative (A) which has been purified by reprecipitation, the production of a desired polyphenylene ether derivative (A) can be confirmed by IR analysis showing that the peak of the primary amino group at 3,300 to 3,500 cm^{-1} has disappeared and that a peak of the carbonyl group of maleimide appears at 1,700 to 1,730 cm^{-1} .

[0044]

The resin composition of the present invention tends to be more excellent in adhesion to conductor, heat resistance, thermal expansion coefficient, flame retardancy and workability (in drilling, cutting) than the resin composition containing the polyphenylene ether compound (A") and the component (B) to be mentioned below.

[0045]

(Thermosetting Resin (B))

The resin component (B) contained in the resin composition of the present invention is at least one thermosetting resin selected from the group consisting of an epoxy resin, a cyanate resin and a maleimide compound. The maleimide compound does not include the above-mentioned polyphenylene ether derivative (A).

The component (B) may be at least one thermosetting resin selected from the group consisting of an epoxy resins and a maleimide compound.

[0046]

The epoxy resin may be an epoxy resin having two or more epoxy groups in one molecule. Here, the epoxy resin is grouped into a glycidyl ether-type epoxy resin, a glycidylamine-type epoxy resin, a glycidyl ester-type epoxy resin, etc. Among these, a glycidyl ether-type epoxy resin may be selected.

The epoxy resin is grouped into various types of epoxy resins depending on the difference in the main skeleton, and various types of the epoxy resins mentioned above may be further grouped into a bisphenol-type epoxy resin such as a bisphenol A-type epoxy resin, a bisphenol F-type epoxy resin, a bisphenol S-type epoxy resin, etc.; an alicyclic epoxy resin; an aliphatic linear epoxy resin; a novolak-type epoxy resin such as a phenol-novolak-type epoxy resin, a cresol-novolak-type epoxy resin, a bisphenol A-novolak-type epoxy resin, a bisphenol F-novolak-type epoxy resin, etc.; a phenol-aralkyl-type epoxy resin, a stilbene-type epoxy resin, a dicyclopentadiene-type epoxy resin, a naphthalene skeleton-containing epoxy resin such as a naphthol-novolak-type epoxy resin, a naphthol-aralkyl-type epoxy resin, etc.; a biphenyl-type epoxy resin, a biphenylaralkyl-type epoxy resin; a xylylene-type epoxy resin; a dihydroanthracene-type epoxy resin; a dicyclopentadiene-type epoxy resin, etc.

One alone or two or more kinds of epoxy resins may be used either singly or as combined. Among these, from the viewpoint of high frequency properties, heat resistance, glass transition temperature, thermal expansion coefficient and flame retardancy, a naphthalene skeleton-containing epoxy resin and a biphenylaralkyl-type epoxy resin may be used.

[0047]

In the case where an epoxy resin is used as the component (B), if desired, a curing agent or a curing aid for epoxy resin may be used as combined. Examples of these include, though not specifically limited thereto, polyamine compounds such as diethylenetriamine, triethylenetetramine, diaminodiphenylmethane,

m-phenylenediamine, dicyandiamide, etc.; polyphenol compounds such as bisphenol A, phenol-novolak resin, cresol-novolak resin, bisphenol A-novolak resin, phenolaralkyl resin, etc.; acid anhydrides such as phthalic anhydride, pyromellitic anhydride, etc.; carboxylic acid compounds; active ester compounds, etc. One alone or two or more of these may be used either singly or as combined. The amount thereof to be used is not specifically limited and may be adequately controlled depending on the object. Among these, from the viewpoint of heat resistance, glass transition temperature, thermal expansion coefficient, storage stability and insulation reliability, polyphenol compounds and active ester compounds may be used.

[0048]

Examples of the cyanate resin include, though not specifically limited thereto, 2,2-bis(4-cyanatophenyl)propane, bis(4-cyanatophenyl)ethane, bis(3,5-dimethyl-4-cyanatophenyl)methane, 2,2-bis(4-cyanatophenyl)-1,1,1,3,3,3-hexafluoropropane, α,α' -bis(4-cyanatophenyl)-m-diisopropylbenzene, cyanate ester compound of phenol-added dicyclopentadiene polymer, phenol-novolak-type cyanate ester compound and cresol-novolak-type cyanate ester compound. One alone or two or more kinds of cyanate resins may be used either singly or as combined. Among these, from the viewpoint of production cost as well as from the viewpoint of total balance of high frequency properties and other properties, 2,2-bis(4-cyanatophenyl)propane may be used.

[0049]

In the case where a cyanate resin is used as the component (B), if desired, a curing agent or a curing aid for cyanate resin may be used as combined. Examples of these include, though not specifically limited thereto, monophenol compounds, polyphenol compounds, amine compounds, alcohol compounds, acid anhydrides, carboxylic acid compounds, etc. One alone or two or more of these may be used either singly or as combined. The amount of the curing agent and the curing aid to be used is not specifically limited and may be adequately controlled depending on the object. Among these, from the viewpoint of high frequency properties, heat resistance, moisture absorption resistance and storage stability, monophenol compounds may be used.

In the case where a cyanate resin is used as combined with a monophenol compound, from the viewpoint of solubility in organic solvent, a method of

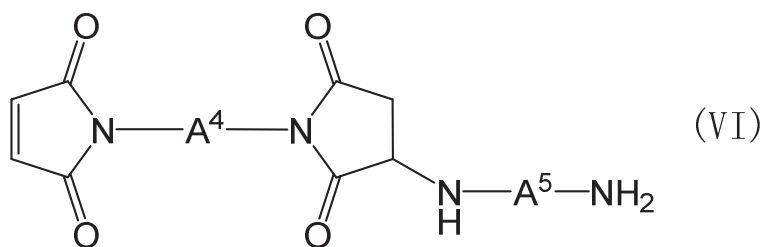
pre-reacting them to give a phenol-modified cyanate prepolymer may be employed. Regarding the monophenol compound to be used in combination, all the prescribed amount thereof may be incorporated in prepolymerization, or the prescribed amount may be divided in portions and added portionwise before and after prepolymerization, but from the viewpoint of storage stability, the method of portionwise incorporating the compound may be employed.

[0050]

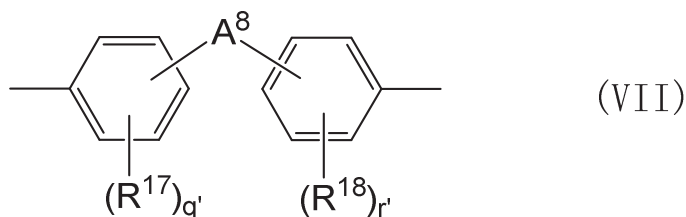
The maleimide compound is not specifically limited, but, for example, at least one of (a) a polymaleimide compound having at least two N-substituted maleimide groups in one molecule [hereinafter this may be referred to as component (a)] and (c) a polyaminobismaleimide compound represented by the following general formula (VI) [hereinafter this may be referred to as component (c)] may be contained. From the viewpoint of solubility in organic solvent, high frequency properties, adhesion to conductor and prepreg formability, the maleimide compound may be the polyaminobismaleimide compound (c).

The polyaminobismaleimide compound (c) may be obtained, for example, by reacting the component (a) and an aromatic diamine compound (b) having two primary amino groups in one molecule [hereinafter this may be referred to as component (b)] in a mode of Michael addition reaction in an organic solvent:

[0051]



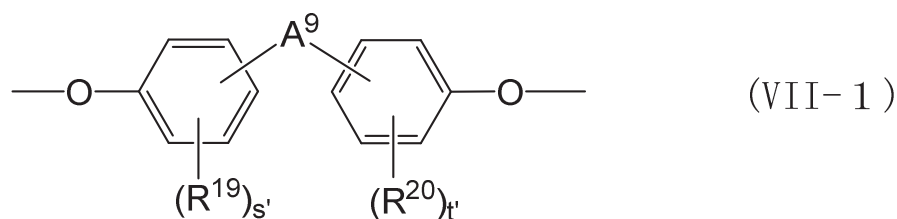
wherein A^4 has the same definition as A^1 in the above general formula (Z), and A^5 is a group represented by the following general formula (VII):



wherein R^{17} and R^{18} each independently represent an aliphatic hydrocarbon group having 1 to 5 carbon atoms, an alkoxy group having 1 to 5 carbon atoms, a hydroxyl group or a halogen atom, A^8 represents an alkylene

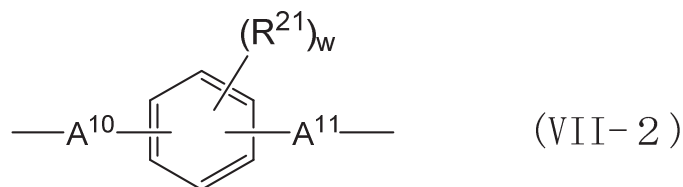
group having 1 to 5 carbon atoms, an alkylidene group having 2 to 5 carbon atoms, an ether group, a sulfide group, a sulfonyl group, a carbonyloxy group, a keto group, a fluorenylene group, a single bond, or a group represented by the following general formula (VII-1) or (VII-2), and q' and r' each independently represent an integer of 0 to 4:

[0052]



wherein R^{19} and R^{20} each independently represent an aliphatic hydrocarbon group having 1 to 5 carbon atoms, or a halogen atom, A^9 represents an alkylene group having 1 to 5 carbon atoms, an isopropylidene group, an m-phenylenediisopropylidene group, a p-phenylenediisopropylidene group, an ether group, a sulfide group, a sulfonyl group, a carbonyloxy group, a keto group or a single bond, and s' and t' each independently represent an integer of 0 to 4:

[0053]



wherein R^{21} represents an aliphatic hydrocarbon group having 1 to 5 carbon atoms, or a halogen atom, A^{10} and A^{11} each independently represent an alkylene group having 1 to 5 carbon atoms, an isopropylidene group, an ether group, a sulfide group, a sulfonyl group, a carbonyloxy group, a keto group or a single bond, and w represents an integer of 0 to 4.

[0054]

The aliphatic hydrocarbon group having 1 to 5 carbon atoms and the halogen atom that R^{17} , R^{18} , R^{19} , R^{20} and R^{21} in the above general formula (VII), (VII-1) or (VII-2) represent include the same ones as those of R^1 in the general formula (I). The aliphatic hydrocarbon group may be an aliphatic hydrocarbon group having 1 to 3 carbon atoms, and may be a methyl group or an ethyl group.

A^4 in the general formula (VI) have the same definition as A^1 in the general formula (Z).

The alkylene group having 1 to 5 carbon atoms that A⁸ and A⁹ in the above general formula (VII), (VII-1) or (VII-2) represent, and the alkylidene group having 2 to 5 carbon atoms that A⁸ represents may be described in the same manner as that for the case of A² in the general formula (III). The alkylene group having 1 to 5 carbon atoms that A¹⁰ and A¹¹ in the general formula (VII-2) represent may be described in the same manner as that for the case of A² in the general formula (III).

q' and r' each are an integer of 0 to 4, and from the viewpoint of easy availability, both may be an integer of 0 to 2, or may be 0 or 2. s' and t' each are an integer of 0 to 4, and from the viewpoint of easy availability, both may be an integer of 0 to 2, or may be 0 or 1, or may be 0. w is an integer of 0 to 4, and from the viewpoint of easy availability, may be an integer of 0 to 2, or may be 0.

[0055]

The component (a) is not specifically limited, but for example, the same ones as those of the above-mentioned bismaleimide compound (IX) are applicable. Examples of the component (a) include bis(4-maleimidophenyl)methane, polyphenylmethanemaleimide, bis(4-maleimidophenyl) ether, bis(4-maleimidophenyl) sulfone, 3,3'-dimethyl-5,5'-diethyl-4,4'-diphenylmethanebismaleimide, 4-methyl-1,3-phenylenebismaleimide, m-phenylenebismaleimide, 2,2-bis(4-(4-maleimidophenoxy)phenyl)propane, bis(4-maleimidophenyl) sulfone, bis(4-maleimidophenyl) sulfide, bis(4-maleimidophenyl) ketone, 2,2-bis(4-(4-maleimidophenoxy)phenyl)propane, bis(4-(4-maleimidophenoxy)phenyl) sulfone, 4,4'-bis(3-maleimidophenoxy)biphenyl, 1,6-bismaleimido-(2,2,4-trimethyl)hexane, etc. These may be used individually or in combination, depending on the object and use. The component (a) may be a bismaleimide compound, and may be bis(4-maleimidophenyl)methane from the viewpoint of inexpensiveness, may be 3,3'-dimethyl-5,5'-diethyl-4,4'-diphenylmethanebismaleimide from the viewpoint of excellent dielectric properties and low water absorption, and may be 2,2-bis(4-(4-maleimidophenoxy)phenyl)propane from the viewpoint of high adhesion to conductor and excellent mechanical properties (elongation, strength at break).

[0056]

As described above, the polyaminobismaleimide compound (c) may be

obtained by reacting the above component (a) and an aromatic diamine compound (b) having two primary amino groups in one molecule in an organic solvent in a mode of Michael addition reaction.

[0057]

Examples of the component (b) include, though not specifically limited thereto, 4,4'-diaminodiphenylmethane, 4,4'-diamino-3,3'-dimethyl-diphenylmethane, 4,4'-diamino-3,3'-diethyl-diphenylmethane, 4,4'-diaminodiphenyl ether, 4,4'-diaminodiphenyl sulfone, 3,3'-diaminodiphenyl sulfone, 4,4'-diaminodiphenyl ketone, 4,4'-diaminobiphenyl, 3,3'-dimethyl-4,4'-diaminobiphenyl, 2,2'-dimethyl-4,4'-diaminobiphenyl, 3,3'-dihydroxybenzidine, 2,2-bis(3-amino-4-hydroxyphenyl)propane, 3,3'-dimethyl-5,5'-diethyl-4,4'-diphenylmethanediamine, 2,2-bis(4-aminophenyl)propane, 2,2-bis(4-(4-aminophenoxy)phenyl)propane, 1,3-bis(3-aminophenoxy)benzene, 1,3-bis(4-aminophenoxy)benzene, 1,4-bis(4-aminophenoxy)benzene, 4,4'-bis(4-aminophenoxy)biphenyl, 1,3-bis(1-4-(4-aminophenoxy)phenyl)-1-methylethyl)benzene, 1,4-bis(1-4-(4-aminophenoxy)phenyl)-1-methylethyl)benzene, 4,4'-[1,3-phenylenebis(1-methylethylidene)]bis(aniline), 4,4'-[1,4-phenylenebis(1-methylethylidene)]bis(aniline), 3,3'-[1,3-phenylenebis(1-methylethylidene)]bis(aniline), bis(4-(4-aminophenoxy)phenyl) sulfone, bis(4-(3-aminophenoxy)phenyl) sulfone, 9,9-bis(4-aminophenyl)fluorene, etc. These components (b) may be used individually or in combination.

Among these, from the viewpoint of achieving high solubility in an organic solvent and high reaction rate for the synthesis as well as high heat resistance, the component may be selected from 4,4'-diaminodiphenylmethane, 4,4'-diamino-3,3'-dimethyl-diphenylmethane, 4,4'-diamino-3,3'-diethyl-diphenylmethane, 2,2-bis(4-(4-aminophenoxy)phenyl)propane, 4,4'-[1,3-phenylenebis(1-methylethylidene)]bis(aniline), and 4,4'-[1,4-phenylenebis(1-methylethylidene)]bis(aniline). From the viewpoint of the inexpensiveness in addition to the above-mentioned high solubility, high reaction rate, and high heat resistance, the component may be 4,4'-diaminodiphenylmethane, 4,4'-diamino-3,3'-dimethyl-diphenylmethane, or

4,4'-diamino-3,3'-diethyl-diphenylmethane. Further, from the viewpoint of achieving high adhesion to conductor in addition to the above-mentioned high solubility, high reaction rate, and high heat resistance, the compound may be 2,2-bis(4-(4-aminophenoxy)phenyl)propane,

4,4'-[1,3-phenylenebis(1-methylethylidene)]bisaniiline, or
 4,4'-[1,4-phenylenebis(1-methylethylidene)]bisaniiline. Furthermore, from the viewpoint of achieving excellent high-frequency properties and moisture absorption resistance in addition to the above-mentioned high solubility, high reaction rate, high heat resistance, and high adhesion to conductor, the component may be selected from 4,4'-[1,3-phenylenebis(1-methylethylidene)]bisaniiline and 4,4'-[1,4-phenylenebis(1-methylethylidene)]bisaniiline. According to the object and use, these may be used individually or in combination.

[0058]

With respect to the organic solvent used in producing the polyaminobismaleimide compound (c), there is no particular limitation. However, for example, the organic solvents mentioned above as examples in connection with the production step for the polyphenylene ether compound (A") can be applied. These may be used individually or in combination. Of these, methyl ethyl ketone, cyclohexanone, propylene glycol monomethyl ether, N,N-dimethylformamide, and N,N-dimethylacetamide may be used from the viewpoint of solubility.

[0059]

With respect to the amounts of the component (a) and the component (b) used in producing the component (c), the component (a) and the component (b) may be incorporated so that the equivalent ratio (Tb_2/Ta_2) of the maleimide group equivalent (Tb_2) of the component (a) to the $-NH_2$ group equivalent (Ta_2) of the component (b) could be in the range of 1 to 10, or could be in the range of 2 to 10. When the component (a) and component (b) are used so that the equivalent ratio could be in the above range, the resin composition, the prepreg and the laminate of the present invention can have excellent high frequency properties, high adhesion to conductor, excellent heat resistance, high glass transition temperature and powerful flame retardancy.

[0060]

A reaction catalyst may not be used for the Michael addition reaction in producing the polyaminobismaleimide compound (c), but may be used as needed.

The reaction catalyst is not specifically limited, and the reaction catalyst usable in the Michael addition reaction in producing the above-mentioned polyphenylene ether derivative (A) is applicable. Also as described above, the amount of the reaction catalyst to be incorporated is not specifically limited.

[0061]

In the case where a maleimide compound is used as the component (B), a curing agent for the maleimide compound, a crosslinking agent, a curing aid and other may be used. These are not specifically limited, and examples thereof include vinyl compounds such as styrene monomer, divinylbenzene, divinylbiphenyl, etc.; (meth)acrylate compounds; allyl compounds such as triallyl cyanurate, triallyl isocyanurate, etc.; polyamine compounds such as diaminodiphenylmethane, etc. One alone or two or more of these may be used either singly or as combined. The amount of these to be used is not also specifically limited, and may be adequately controlled depending on the object. Among these, from the viewpoint of high frequency properties and heat resistance, vinyl compounds or polyamine compounds may be used.

[0062]

The above-mentioned component (a) and component (b) and an organic solvent and optionally a reaction catalyst and others are put into a reactor each in a predetermined amount, and with heating, keeping the heat and stirring, these are reacted in a mode of Michael addition reaction to give the polyaminobismaleimide compound (c). For the reaction conditions in this step, for example, the reaction conditions in the Michael addition reaction in producing the above-mentioned polyphenylene ether derivative (A) are applicable.

The reaction concentration (solid concentration) is not specifically limited, but may be 10 to 90% by mass, and may be 20 to 80% by mass. When the reaction concentration is 10% by mass or more, the reaction speed is not too low, and tends to be advantageous from the viewpoint of production cost. When the reaction concentration is 90% by mass or less, better solubility tends to be attained. If so, in addition, the solution viscosity may be low and the stirring efficiency tends to be good to suppress gelation. After production of the polyaminobismaleimide compound (c), a part or all of the organic solvent may be removed (for concentration), or an additional organic solvent may be added for dilution in accordance with the intended object, like in producing the polyphenylene ether derivative (A).

[0063]

(Content of Component (A) and Component (B), and Content Ratio Thereof)

The content of the component (A) is not specifically limited, but is, from the viewpoint of high frequency properties, preferably 3% by mass or more relative to 100 parts by mass of the sum total of the components (A) to (C), more preferably 5% by mass or more.

The content of the component (B) is not specifically limited, but is, from the viewpoint of high frequency properties and formability, preferably 10 to 90% by mass relative to 100 parts by mass of the sum total of the components (A) to (C), more preferably 20 to 80% by mass.

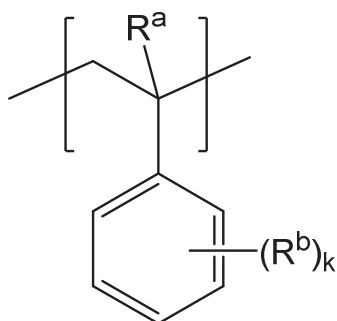
The content ratio of the component (A) to the component (B) [(A)/(B)] is not specifically limited, and may be 5/95 to 80/20 by mass, may be 5/95 to 75/25, may be 5/95 to 70/30, and may be 10/90 to 70/30. When the content ratio of the component (A) to the total content of the component (A) and the component (B) is 5% by mass or more, more excellent high frequency properties and low moisture absorption tend to be attained. When the ratio is 80% by mass or less, more excellent heat resistance, more excellent formability and more excellent workability tend to be attained.

[0064]

(Styrenic Thermoplastic Elastomer (C))

The component (C) contained in the resin composition of the present invention is a styrenic thermoplastic elastomer. Containing the component (C), the resin composition of the present invention has good and well-balanced formability, high frequency properties (dielectric properties), adhesion to conductor, soldering heat resistance, glass transition temperature, thermal expansion coefficient and flame retardancy.

Not specifically limited, the styrenic thermoplastic elastomer (C) may be any thermoplastic elastomer having a structural unit (see below) derived from a styrenic compound represented by the following general formula, and may be a thermoplastic elastomer having a styrene-derived structural unit (R^a = hydrogen atom, $k = 0$).



(Styrene Compound-Derived Structural Unit)

In the formula, R^a represents a hydrogen atom, or an alkyl group having 1 to 5 carbon atoms, R^b represents an alkyl group having 1 to 5 carbon atoms, k represents an integer of 0 to 5.

Examples of the alkyl group having 1 to 5 carbon atoms that R^a and R^b represent include a methyl group, an ethyl group, an n-propyl group, etc., and the group may be an alkyl group having 1 to 3 carbon atoms, or may be a methyl group.

R^a may be a hydrogen atom.

k may be an integer of 0 to 2, or may be 0 or 1, or may be 0.

[0065]

The other structural unit than the styrenic compound-derived structural unit that the styrenic thermoplastic elastomer (C) has includes a butadiene-derived structural unit, an isoprene-derived structural unit, a maleic acid-derived structural unit, a maleic anhydride-derived structural unit, etc. One alone or two more kinds of styrenic thermoplastic elastomers (C) may be used either singly or as combined.

The butadiene-derived structural unit and the isoprene-derived structural unit may be hydrogenated. In the case of hydrogenation, the butadiene-derived structural unit is a structural unit of a mixture of an ethylene unit and a butylene unit, and the isoprene-derived structural unit is a structural unit of a mixture of an ethylene unit and a propylene unit.

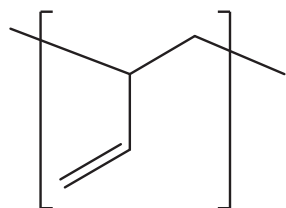
[0066]

From the viewpoint of high frequency properties (low dielectric constant, low dielectric dissipation factor), adhesion to conductor, heat resistance, glass transition temperature and thermal expansion coefficient, the styrenic thermoplastic elastomer (C) may be at least one selected from a styrene-butadiene-styrene block copolymer hydrogenate (SEBS, SBBS), a

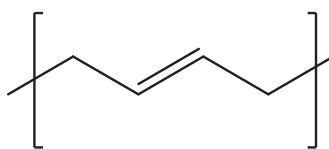
styrene-isoprene-styrene block copolymer hydrogenate (SEPS) and a styrene-maleic anhydride copolymer (SMA).

[0067]

The styrene-butadiene-styrene block copolymer hydrogenate includes SEBS where the hydrogenation ratio of the carbon-carbon double bonds is generally 90% or more (or may be 95% or more), and SBBS where the carbon-carbon double bond at the 1,2-bond site in the butadiene block (see the left side of the following) has been partially hydrogenated (the hydrogenation ratio to all carbon-carbon double bonds is about 60 to 85%).



C-C double bond at 1,2-bond site



C-C double bond at 1,4-bond site

[0068]

In SEBS, the content of the styrene-derived structural unit (hereinafter this may be abbreviated as styrene content) may be, from the viewpoint of high frequency properties (low dielectric constant, low dielectric dissipation factor), adhesion to conductor, heat resistance, glass transition temperature and thermal expansion coefficient, 5 to 80% by mass, or may be 5 to 70% by mass, or may be 10 to 70% by mass, or may be 10 to 50% by mass. The melt flow rate (MFR) of SEBS may be, though not specifically limited thereto, 0.1 to 20 g/10 min under the measurement condition at 230°C and a load of 2.16 kgf (21.2 N), or may be 0.5 to 15 g/10 min.

Examples of commercial products of SEBS include Tuftec (registered trademark) H Series and M Series manufactured by Asahi Kasei Chemicals Corporation, Septon (registered trademark) Series manufactured by Kuraray Co., Ltd., Crayton (registered trademark) G Polymer Series manufactured by Crayton Polymer Japan Corporation, etc.

The styrene content in SBBS may be, from the viewpoint of high frequency properties (low dielectric constant, low dielectric dissipation factor), adhesion to conductor, heat resistance, glass transition temperature and thermal expansion, 40 to 80% by mass, or may be 50 to 75% by mass, or may be 55 to 75% by mass. The melt flow rate (MFR) of SBBS may be, though not specifically limited thereto,

0.1 to 10 g/10 min under the measurement condition at 190°C and a load of 2.16 kgf (21.2 N), or may be 0.5 to 10 g/10 min, or may be 1 to 6 g/10 min.

Examples of commercial products of SBBS include Tuftec (registered trademark) P Series manufactured by Asahi Kasei Chemicals Corporation, etc.

[0069]

The hydrogenation ratio of the styrene-isoprene-styrene block copolymer hydrogenate (SEPS) may be 90% or more, or may be 95% or more. In SEPS, the styrene content may be, from the viewpoint of high frequency properties (low dielectric constant, low dielectric dissipation factor), adhesion to conductor, heat resistance, glass transition temperature and thermal expansion, 5 to 60% by mass, or may be 5 to 50% by mass, or may be 10 to 40% by mass. The melt flow rate (MFR) of SEPS may be, though not specifically limited thereto, 0.1 to 130 g/10 min under the measurement condition at 230°C and a load of 2.16 kgf (21.2 N), or may be 10 to 100 g/10 min, or may be 50 to 90 g/10 min.

Examples of commercial products of SEPS include Septon (registered trademark) Series manufactured by Kuraray Co., Ltd., Crayton G Polymer Series manufactured by Crayton Polymer Japan Corporation, etc.

[0070]

In the styrene-maleic anhydride copolymer (SMA), the styrene content may be, from the viewpoint of high frequency properties (low dielectric constant, low dielectric dissipation factor), adhesion to conductor, heat resistance, glass transition temperature and thermal expansion coefficient, 20 to 90% by mass, or may be 40 to 90% by mass, or may be 50 to 90% by mass, or may be 55 to 85% by mass.

In the styrene-maleic anhydride copolymer (SMA), the maleic anhydride-derived structural unit may be esterified.

Examples of commercial products of SMA include SMA (registered trademark) Resin manufactured by Cray Valley Technology USA, etc.

For all the styrenic thermoplastic elastomers (C), commercial products may be used. The styrene content and the melt flow rate (MFR) mentioned above are the values described in the manufacturer's catalogue or homepages.

[0071]

The content ratio of the component (C) may be, from the viewpoint of high frequency properties (low dielectric constant, low dielectric dissipation factor), adhesion to conductor, heat resistance, glass transition temperature and thermal

expansion coefficient, 5 to 60 parts by mass relative to 100 parts by mass of the sum total of the components (A) to (C), or may be 10 to 60 parts by mass, or may be 15 to 60 parts by mass, or may be 15 to 50 parts by mass, or may be 15 to 40 parts by mass. When the content ratio of the component (C) is 5 parts by mass or more relative to 100 parts by mass of the sum total of the components (A) to (C), high frequency properties and moisture absorption resistance tend to be better, and when 60 parts by mass or less, heat resistance, formability, workability and flame retardancy tend to be better.

[0072]

<Other Components>

The resin composition of the present invention, if necessary, may contain at least one component selected from an inorganic filler (D) [hereinafter, frequently referred to as “component (D)”], a curing accelerator (E) [hereinafter, frequently referred to as “component (E)”] and a flame retardant (F) [hereinafter, frequently referred to as “component (F)”]. By virtue of containing these components, a laminate obtained using the resultant resin composition can be further improved in various properties.

For example, an appropriate inorganic filler (D) optionally incorporated in the resin composition of the present invention can improve low thermal expansion coefficient, high modulus of elasticity, heat resistance and flame retardancy. An appropriate curing accelerator (E) incorporated in the resin composition can improve the curability of the resin composition and therefore can improve high frequency properties, heat resistance, adhesion to conductor, modulus of elasticity and glass transition temperature. Further, a flame retardant (F) and optionally a flame retardant promoter incorporated in the resin composition can improve the flame retardancy of the composition.

[0073]

(Inorganic Filler (D))

The component (D) is not specifically limited, but examples thereof include silica, alumina, titanium oxide, mica, beryllia, barium titanate, potassium titanate, strontium titanate, calcium titanate, aluminum carbonate, magnesium hydroxide, aluminum hydroxide, aluminum silicate, calcium carbonate, calcium silicate, magnesium silicate, silicon nitride, boron nitride, clay (calcined clay, etc.), talc, aluminum borate, aluminum borate, silicon carbide, etc. These may be used individually or in combination. Among these, from the viewpoint of thermal

expansion coefficient, modulus of elasticity, heat resistance and flame retardancy, the component may be silica, alumina, mica or talc, or may be silica or alumina, or may be silica. Examples of silica include a precipitated silica produced according to a wet method and having a high water content, and a dry-method silica produced according to a dry method and containing little bound water, and further, the dry-method silica includes ground silica, fumed silica and molten silica (molten spherical silica) as grouped depending on the difference in the production method.

With respect to the shape and the particle diameter of the inorganic filler (D), there is no particular limitation, but, for example, the particle size may be 0.01 to 20 μm , or may be 0.1 to 10 μm . The term “particle diameter” used here indicates an average particle diameter, which corresponds to a particle diameter determined at a point of 50% volume in a cumulative frequency distribution curve obtained from the particle diameters when the whole volume of the particles is taken as 100%. The particle diameter can be measured by means of a particle size distribution measurement apparatus using a laser diffraction scattering method or the like.

[0074]

In the case where the component (D) is used, the content ratio of the component (D) in the resin composition is not specifically limited, but from the viewpoint of thermal expansion coefficient, modulus of elasticity, heat resistance and flame retardancy, the content ratio of the component (D) in the resin composition may be 3 to 65% by volume, or may be 5 to 60%, or may be 15 to 55% by volume. When the content ratio of the component (D) in the resin composition falls within the above range, better curability, formability and chemical resistance tend to be attained.

In addition, in the case where the component (D) is used, if desired, a coupling agent may be used together with it for the purpose of improving the dispersibility of the component (D) and improving the adhesion between the component (D) and the organic component in the resin composition. The coupling agent is not specifically limited, and for example, a silane coupling agent or a titanate coupling agent may be adequately selected and used. One alone or two or more kinds of coupling agents may be used either singly or as combined. The amount of the coupling agent to be used is not also specifically limited, and for example, the amount may be 0.1 to 5 parts by mass relative to 100 parts by

mass of the component (D), or may be 0.5 to 3 parts by mass. Within the range, various properties can be prevented from degrading and the characteristics by the use of the component (D) tend to be effectively exhibited.

In the case where a coupling agent is used, a system of using an inorganic filler that has been previously surface-treated in dry or wet with a coupling agent may be employed, but not a so-called integral blending system where the component (D) is first incorporated in the resin composition and then a coupling agent is added thereto. Employing the former system promotes effective expression of the characteristics of the component (D).

[0075]

In the case where the component (D) is used in the present invention, if desired, the component (D) may be previously dispersed in an organic solvent to be a slurry for the purpose of improving the dispersibility of the component (D) in the resin composition. The organic solvent to be used in forming the component (D) into a slurry is not specifically limited, and for example, the organic solvents exemplified hereinabove in the production step for the polyphenylene ether compound (A") are applicable. One alone or two or more kinds of these may be used either singly or as combined. Among these, from the viewpoint of dispersibility, methyl ethyl ketone, methyl isobutyl ketone and cyclohexanone may be selected. The solid content (nonvolatile content) concentration of the slurry is not specifically limited, but for example, from the viewpoint of precipitation and dispersion performance of the inorganic filler (D), the concentration may be 50 to 80% by mass, or may be 60 to 80% by mass.

[0076]

(Curing Accelerator (E))

In the case where the component (E) is contained in the resin composition of the present invention, a suitable component (E) may be used in accordance with the kind of the component (B) to be used.

In the case where an epoxy resin is used as the component (B), examples of the component (E) include imidazole compounds and derivatives thereof; tertiary amine compounds; quaternary ammonium compounds; phosphorus compounds such as triphenyl phosphine, etc. One alone or two or more kinds of these may be used either singly or as combined. Among these, from the viewpoint of heat resistance, glass transition temperature and storage stability, imidazole compounds and derivatives thereof or phosphorus compounds may be

used. Examples of the imidazole compounds include methylimidazole, phenylimidazole, isocyanate-masked imidazole (for example, addition reaction product of hexamethylene diisocyanate resin and 2-ethyl-4-methylimidazole, etc.) and others, and isocyanate-masked imidazole may be selected.

[0077]

Examples of the component (E) in the case where an isocyanate resin is used as the component (B) include imidazole compounds and derivatives thereof; carboxylates with manganese, cobalt, zinc or the like; organic metal compounds such as acetylacetone complexes with a transition metal of manganese, cobalt, zinc or the like, etc. One alone or two or more kinds of these may be used either singly or as combined. Among these, from the viewpoint of heat resistance, glass transition temperature and storage stability, organic metal compounds may be used.

[0078]

Examples of the component (E) in the case where a maleimide compound is used as the component (B) include acidic catalysts such as p-toluenesulfonic acid, etc.; amine compounds such as triethylamine, pyridine, tributylamine, etc.; imidazole compounds such as methylimidazole, phenylimidazole, isocyanate-masked imidazole (for example, addition reaction product of hexamethylene diisocyanate resin and 2-ethyl-4-methylimidazole); tertiary amine compounds; quaternary ammonium compounds; phosphorus compounds such as triphenyl phosphine, etc.; organic peroxides such as dicumyl peroxide, 2,5-dimethyl-2,5-bis(t-butylperoxy)hexyne-3,2,5-dimethyl-2,5-bis(t-butylperoxy)hexane, t-butylperoxyisopropyl monocarbonate, α,α' -bis(t-butylperoxy)diisopropylbenzene, etc.; carboxylates with manganese, cobalt, zinc or the like, etc. One alone or two or more kinds of these may be used either singly or as combined. Among these, from the viewpoint of heat resistance, glass transition temperature and storage stability, imidazole compounds, organic peroxides and carboxylates may be used; or from the viewpoint of heat resistance, glass transition temperature, modulus of elasticity and thermal expansion coefficient, an imidazole compound may be used in combination with an organic peroxide or a carboxylate. Among organic peroxides, α,α' -bis(t-butylperoxy)diisopropylbenzene may be selected, and among carboxylates, manganese naphthenate may be selected.

[0079]

In the case where the component (E) is contained in the resin composition of the present invention, the content ratio of the component (E) is not specifically limited, but for example, the ratio may be 0.01 to 10 parts by mass relative to 100 parts by mass of the sum total of the components (A) and the component (B) in the present invention, or may be 0.01 to 5 parts by mass. Using the component (E) in the range tends to secure better heat resistance and storage stability.

[0080]

(Flame Retardant (F))

The component (F) includes phosphorus flame retardants, metal hydrates, halogen flame retardants, etc. From the viewpoint of environmental issues, phosphorus flame retardants and metal hydrates may be used. One alone or two or more kinds of flame retardants (F) may be used either singly or as combined.

[0081]

- Phosphorus Flame Retardant -

The phosphorus flame retardant for use herein is not specifically limited and may be any ordinary flame retardant containing a phosphorus atom, including inorganic phosphorus flame retardants and organic phosphorus flame retardants. From the viewpoint of environmental issues, those not containing a halogen atom may be selected. From the viewpoint of high frequency properties (low dielectric constant, low dielectric dissipation factor), adhesion to conductor, heat resistance, glass transition temperature, thermal expansion coefficient and flame retardancy, organic phosphorus flame retardants may be used.

Examples of the inorganic phosphorus flame retardants include red phosphorus; ammonium phosphates such as monoammonium phosphate, diammonium phosphate, triammonium phosphate, ammonium polyphosphate, etc.; inorganic nitrogen-containing phosphorus compounds such as phosphoric amide, etc.; phosphoric acid; phosphine oxide, etc.

Examples of the organic phosphorus flame retardants include aromatic phosphates, monosubstituted phosphonic diesters, disubstituted phosphinates, metal salts of disubstituted phosphinic acids, organic nitrogen-containing phosphorus compounds, cyclic organic phosphorus compounds, etc. Among these, aromatic phosphate compounds, and metal salts of disubstituted phosphinic acids may be selected. Here, metal salts may be any of lithium salts, sodium salts, potassium salts, calcium salts, magnesium salts, aluminum salts, titanium salts, and zinc salts, or may be aluminum salts. Among the organic phosphorus flame

retardants, aromatic phosphates may be selected.

[0082]

Examples of the aromatic phosphates include triphenyl phosphate, tricresyl phosphate, trixylenyl phosphate, cresyldiphenyl phosphate, cresyl di-2,6-xylenyl phosphate, resorcinol bis(diphenyl phosphate), 1,3-phenylenebis(di-2,6-xylenyl phosphate), bisphenol A bis(diphenyl phosphate), 1,3-phenylenebis(diphenyl phosphate), etc.

Examples of the monosubstituted phosphonic diesters include divinyl phenylphosphonate, diallyl phenylphosphonate, bis(1-butenyl) phenylphosphonate, etc.

Examples of the disubstituted phosphinates include phenyl diphenylphosphinate, methyl diphenylphosphinate, etc.

Metal salts of disubstituted phosphinic acids include metal salts of dialkylphosphinic acids, metal salts of diallylphosphinic acids, metal salts of divinylphosphinic acids, metal salts of diarylphosphinic acids, etc. These metal salts may be any of lithium salts, sodium salts, potassium salts, calcium salts, magnesium salts, aluminum salts, titanium salts, and zinc salts, and aluminum salts may be selected.

Examples of the organic nitrogen-containing phosphorus compounds include phosphazene compounds such as bis(2-allylphenoxy)phosphazene, dicresylphosphazene, etc.; melamine phosphate; melamine pyrophosphate; melamine polyphosphate; melam polyphosphate, etc.

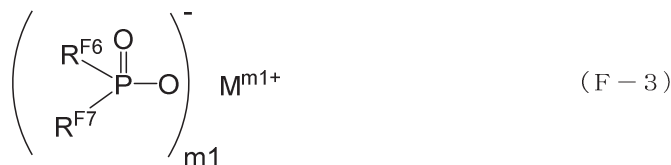
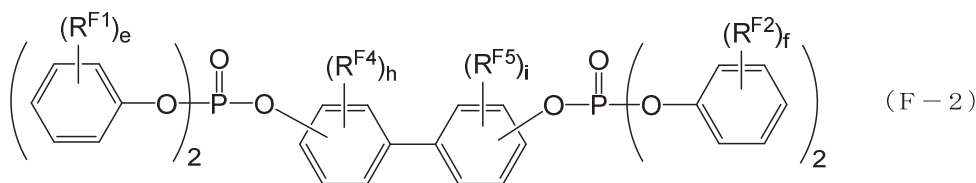
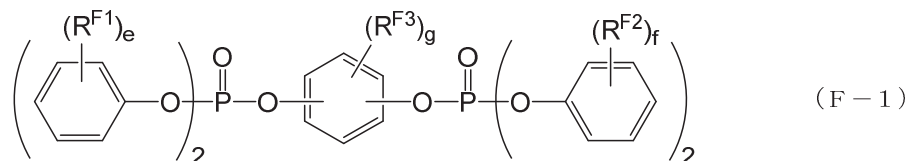
The cyclic organic phosphorus compounds include 9,10-dihydro-9-oxa-10-phosphaphenanthrene-10-oxide, 10-(2,5-dihydroxyphenyl)-9,10-dihydro-9-oxa-10-phosphaphenanthrene-10-oxide, etc.

Among these, at least one may be selected from aromatic phosphates, metal salts of disubstituted phosphinic acids and cyclic organic phosphorus compounds, or at least one may be selected from metal salts of disubstituted phosphinic acids and cyclic organic phosphorus compounds, or a metal salt of a disubstituted phosphinic acid and a cyclic organic phosphorus compound may be used in combination. In particular, the metal salt of a disubstituted phosphinic acid may be a metal salt of a dialkylphosphinic acid, or may be an aluminum salt of a dialkylphosphinic acid. The cyclic organic phosphorus compound may be 10-(2,5-dihydroxyphenyl)-9,10-dihydro-9-oxa-10-phosphaphenanthrene-10-oxide.

In the case where a metal salt of a disubstituted phosphinic acid and a cyclic organic phosphorus compound are used in combination, the blend ratio of the metal salt of a disubstituted phosphinic acid to the cyclic organic phosphorus compound [metal salt of disubstituted phosphinic acid/cyclic organic phosphorus compound] may be 0.6 to 2.5 by mass, or may be 0.9 to 2, or may be 1 to 2, or may be 1.2 to 2.

[0083]

The aromatic phosphates may be aromatic phosphates represented by the following general formula (F-1) or (F-2), and the metal salts of a disubstituted phosphinic acid may be metal salts of a disubstituted phosphinic acid represented by the following general formula (F-3).



[0084]

In the formulae, $\text{R}^{\text{F}1}$ to $\text{R}^{\text{F}5}$ each independently represent an aliphatic hydrocarbon group having 1 to 5 carbon atoms, or a halogen atom. e and f each independently represent an integer of 0 to 5, g , h and i each independently represent an integer of 0 to 4.

$\text{R}^{\text{F}6}$ and $\text{R}^{\text{F}7}$ each independently represent an aliphatic hydrocarbon group having 1 to 5 carbon atoms, or an aromatic hydrocarbon group having 6 to 14 carbon atoms. M represents a lithium atom, a sodium atom, a potassium atom, a calcium atom, a magnesium atom, an aluminum atom, a titanium atom, or a zinc atom. $\text{m}1$ represents an integer of 1 to 4.

[0085]

The aliphatic hydrocarbon group having 1 to 5 carbon atoms and the halogen atom that R^{F1} to R^{F5} represent include the same ones as those of R^1 in the above-mentioned general formula (I).

e and f each may be an integer of 0 to 2, or may be 2. g, h and i each may be an integer of 0 to 2, or may be 0 or 1, or may be 0.

The aliphatic hydrocarbon group having 1 to 5 carbon atoms that R^{F6} and R^{F7} represent include the same ones as those of R^1 in the general formula (I). The aliphatic hydrocarbon group may be an aliphatic hydrocarbon group having 1 to 3 carbon atoms, and may be an ethyl group.

Examples of the aromatic hydrocarbon group having 6 to 14 carbon atoms that R^{F6} and R^{F7} represent include a phenyl group, a naphthyl group, a biphenyl group, an anthryl group, etc. The aromatic hydrocarbon group may be an aromatic hydrocarbon group having 6 to 10 carbon atoms.

m1 represents a valence of a metal ion, that is, it varies within a range of 1 to 4 depending on the kind of M.

M may be an aluminum atom. When M is an aluminum atom, m1 is 3.

[0086]

- Metal Hydrate -

Examples of the metal hydrate include aluminum hydroxide hydrate, magnesium hydroxide hydrate, etc. One alone or two or more kinds of these may be used either singly or as combined. The metal hydroxide may correspond to an inorganic filler, but in the case of a material that imparts flame retardancy, this is grouped in a flame retardant.

[0087]

- Halogen Flame Retardant -

The halogen flame retardant includes a chlorine-based flame retardant, a bromine-based flame retardant, etc. Examples of the chlorine-based flame retardant include paraffin chloride, etc. Examples of the bromine-based flame retardant include brominated epoxy resins such as brominated bisphenol A-type epoxy resin, brominated phenol-novolac-type epoxy resin, etc.; brominated addition-type flame retardants such as hexabromobenzene, pentabromotoluene, ethylenebis(pentabromophenyl), ethylenebis-tetrabromophthalimide, 1,2-dibromo-4-(1,2-dibromoethyl)cyclohexane, tetrabromocyclooctane, hexabromocyclododecane, bis(tribromophenoxy)ethane, brominated

polyphenylene ether, brominated polystyrene, 2,4,6-tris(tribromophenoxy)-1,3,5-triazine, etc. (here, "addition-type" means that bromine has been introduced into the polymer in a form not chemically bonding thereto, that is, bromine has been blended in the polymer); unsaturated double bond group-containing brominated reaction-type flame retardants such as tribromophenylmaleimide, tribromophenyl acrylate, tribromophenyl methacrylate, tetrabromobisphenol A-type dimethacrylate, pentabromobenzyl acrylate, styrene bromide, etc. (here, "reaction-type" means that bromine has been introduced into the polymer in a form chemically bonding thereto), etc. One alone or two or more kinds of these may be used either singly or as combined.

[0088]

(Content Ratio of Component (F))

In the case where a phosphorus flame retardant is used, the content ratio of the phosphorus flame retardant in the resin composition of the present invention is not specifically limited, but for example, the phosphorus atom content in the resin composition in terms of the solid content therein (sum total of the other components than the component (D)) may be 0.2 to 5% by mass, or may be 0.3 to 3% by mass. When the phosphorus atom content is 0.2% by mass or more, better flame retardancy tends to be attained. When the phosphorus atom content is 5% by mass or less, better formability, high adhesion to conductor, excellent heat resistance and high glass transition temperature tend to be attained.

On the other hand, in the case where a halogen flame retardant is contained in the resin composition of the present invention, from the viewpoint of environmental issues and chemical resistance, the content thereof may be 20 parts by mass or less relative to 100 parts by mass of the sum total of the components (A) to (C), or may be 10 parts by mass or less, or may be 5 parts by mass or less.

In the case where any other flame retardant than a phosphorus flame retardant and a halogen flame retardant is contained in the resin composition of the present invention, the content thereof may be, though not specifically limited thereto, 0.5 to 20 parts by mass relative to 100 parts by mass of the sum total of the components (A) to (C), or may be 1 to 15 parts by mass, or may be 1 to 10 parts by mass, or may be 1 to 6 parts by mass.

[0089]

(Flame Retardant Promoter)

The resin composition of the present invention may contain a flame retardant promoter, for example, an inorganic flame retardant promoter such as antimony trioxide, zinc molybdate, etc.

When a flame retardant promoter is contained in the resin composition of the present invention, the content ratio thereof is not specifically limited, but may be, for example, 0.1 to 20 parts by mass relative to 100 parts by mass of the sum total of the component (A) and the component (B), or may be 0.1 to 10 parts by mass. Containing a flame retardant promoter in such a range, the resin composition tends to realize better chemical resistance.

[0090]

If desired, the resin composition of the present invention may adequately contain a resin material such as a known thermoplastic resin, an elastomer, etc., as well as a coupling agent, an antioxidant, a thermal stabilizer, an antistatic agent, a UV absorbent, a pigment, a colorant, a lubricant, etc. One alone or two or more kinds of these may be contained either singly or as combined. The amount of these to be used is not specifically limited.

[0091]

(Organic Solvent)

The resin composition of the present invention may contain an organic solvent, from the viewpoint of easy handleability through dilution and from the viewpoint of easy production of prepreg to be mentioned hereinunder.

Examples of the organic solvent include, though not specifically limited thereto, alcohol solvents such as ethanol, propanol, butanol, methyl cellosolve, butyl cellosolve, propylene glycol monomethyl ether, etc.; ketone solvents such as acetone, methyl ethyl ketone, methyl isobutyl ketone, cyclohexanone, etc.; ether solvents such as tetrahydrofuran, etc.; aromatic solvents such as toluene, xylene, mesitylene, etc.; nitrogen atom-containing solvents such as dimethylformamide, dimethylacetamide, N-methylpyrrolidone, etc.; sulfur atom-containing solvents such as dimethylsulfoxide, etc.; ester solvents such as γ -butyrolactone, etc.

Among these, from the viewpoint of solubility, alcohol solvents, ketone solvents or nitrogen atom-containing solvents may be used, or acetone, methyl ethyl ketone, methyl isobutyl ketone or cyclohexanone may be used, or methyl ethyl ketone may be used.

One alone or two or more kinds of organic solvents may be used either

singly or as combined.

The content of the organic solvent in the resin composition of the present invention is not specifically limited, and the solid concentration may be 30 to 90% by mass, or may be 40 to 80% by mass, or may be 40 to 70% by mass, or may be 40 to 60% by mass. The resin composition whose solid concentration falls within the range secures good handleability and penetrability into substrate, and betters the appearance of prepreg to be produced, and the solid concentration of resin in the prepreg to be mentioned below can be readily controlled, therefore facilitating production of a prepreg having a desired thickness.

[0092]

The above-mentioned components (A) to (C), and the other optional components to be combined, and optionally an organic solvent are mixed in a known method to produce the resin composition of the present invention. In this stage, the components may be dissolved or dispersed with stirring. The conditions for the mixing order, the temperature, the time and others are not specifically limited, and may be defined in any desired manner.

[0093]

The glass transition temperature of the laminate formed with the resin composition of the present invention is not specifically limited, but from the viewpoint of good soldering heat resistance and through-hole interconnection reliability, as well as excellent workability in producing electronic parts and others, the temperature is preferably 200°C or higher. There is no specific limitation in point of the upper limit of the glass transition temperature, and for example, the temperature may be 1,000°C or lower, or may be 500°C or lower, or may be 300°C or lower, or may be 240°C or lower.

The thermal expansion coefficient (in Z direction, not higher than Tg) of the laminate formed with the resin composition of the present invention is not specifically limited, but from the viewpoint of preventing the laminate from warping, the coefficient is preferably 45 ppm/°C or less, more preferably 40 ppm/°C or less. The lower limit of the thermal expansion coefficient is, though not specifically limited thereto, generally 30 ppm/°C or more, preferably 35 ppm/°C or more.

The glass transition temperature and the thermal expansion coefficient are values measured according to IPC Standards, as described in the section of Examples.

[0094]

The dielectric constant and the dielectric dissipation factor of the laminate formed with the resin composition of the present invention are not specifically limited. From the viewpoint of favorable use in a high frequency zone, the dielectric constant at 10 GHz is preferably smaller, and may be 3.85 or less, or may be 3.75 or less, or may be 3.65 or less. The lower limit of the dielectric constant is not specifically limited, and may be, for example, 0.5 or more, or may be 1 or more, or may be 3 or more, or may be 3.4 or more.

The dielectric dissipation factor is preferably smaller, and may be 0.007 or less, or may be 0.006 or less, or may be 0.005 or less. The lower limit of the dielectric dissipation factor is not specifically limited and is preferably smaller, and may be, for example, 0.0001 or more, or may be 0.002 or more, or may be 0.004 or more.

The dielectric constant and the dielectric dissipation factor are values according to JPCA-TM001 (Triplate-line resonator method) as described in the section of Examples.

[0095]

[Prepreg]

The present invention also provides a prepreg containing the resin composition of the present invention and a sheet-form fiber-reinforced substrate. The prepreg is formed using the resin composition of the present invention and a sheet-form fiber-reinforced substrate, and more specifically, the prepreg is formed by impregnating or coating a sheet-form fiber reinforced substrate with the resin composition of the present invention, and drying the substrate. More specifically, for example, the substrate is dried by heating in a drying oven generally at a temperature of 80 to 200°C for 1 to 30 minutes to semi-cure the resin (into a B-stage), thereby producing the prepreg of the present invention. The amount of the resin composition to be used may be defined so that the resin composition-derived solid concentration in the dried prepreg could be 30 to 90% by mass. When the solid content is controlled to fall within the range, the laminate to be obtained using the resultant prepreg can achieve excellent formability.

[0096]

As the sheet-form fiber reinforced substrate for the prepreg, a known substrate used in a laminate for various electrically insulating materials is used. Examples of the materials for the sheet-form reinforced substrate include

inorganic fibers of E glass, D glass, S glass, Q glass or the like; organic fibers of polyimide, polyester, tetrafluoroethylene or the like; mixtures thereof, etc. These sheet-form reinforced substrate may have, for example, a form of woven fabric, nonwoven fabric, roving, chopped strand mat, surfacing mat, etc. With respect to the thickness of the sheet-form fiber reinforced substrate, there is no particular limitation, and, for example, the substrate having a thickness of about 0.02 to 0.5 mm can be used. Further, the substrate having a surface treated with a coupling agent or the like or having a mechanically opening treated substrate can be used from the viewpoint of impregnation performance with the resin composition, and from the viewpoint of heat resistance, moisture absorption resistance, and processability of the laminate formed with the substrate.

[0097]

As the method of impregnating or coating the sheet-form reinforced substrate with the resin composition, a hot melt method or a solvent method to be mentioned below may be employed.

In the hot melt method, an organic solvent is not contained in the resin composition, and the method is (1) a method of once applying the composition onto a releasable sheet, and laminating it on a sheet-form reinforced substrate, or (2) a method of directly applying the resin composition to a sheet-form reinforced substrate using a die coater.

On the other hand, the solvent method is a method of adding an organic solvent to the resin composition, and immersing a sheet-form reinforced substrate in the resultant resin composition so that the sheet-form reinforced substrate could be impregnated with the resin composition, and thereafter drying it.

[0098]

[Laminate and Multilayer Printed Wiring Board]

The laminate of the present invention contains the prepreg of the present invention and a metal foil. The laminate of the present invention is formed using the prepreg of the present invention and a metal foil, and more specifically, the laminate is formed by arranging a metal foil on one surface or both surfaces of one prepreg, or by arranging a metal foil on one surface of both surfaces of a multilayer prepreg prepared by layering two or more prepreps of the present invention, and thereafter molding the resultant structure under heat and pressure.

Not specifically limited, the metal for the metal foil may be any one usable

for electrically insulating materials, but from the viewpoint of electroconductivity, the metal may be copper, gold, silver, nickel, platinum, molybdenum, ruthenium, aluminum, tungsten, iron, titanium, chromium, or an alloy containing at least one of these metal elements, or may be copper or aluminium, or may be copper.

The condition for thermal pressure forming is not specifically limited. For example, the temperature may be 100°C to 300°C, the pressure may be 0.2 to 10.0 MPa, and the time may be 0.1 to 5 hours. For thermal pressure forming, a method of using a vacuum press or the like to keep a vacuum state for 0.5 to 5 hours may be employed.

The multilayer printed wiring board of the present invention is formed using the prepreg or the laminate of the present invention. The multilayer printed wiring board of the present invention can be produced using the prepreg or the laminate of the present invention by performing circuit formation processing and bonding processing for forming a multilayer by perforating, metal plating, etching for a metal foil or the like according to a known method.

[0099]

The resin composition, the resin film, the prepreg, the metal-clad laminate and the multilayer printed wiring board of the present invention are favorably used in electronic devices working with high frequency signals of 1 GHz or more, and are especially favorably used in electronic devices working with high frequency signals of 10 GHz or more.

[0100]

Hereinabove, the preferred embodiments of the present invention were described, but these embodiments are examples used for describing the present invention, and these embodiments should not be construed as limiting the scope of the present invention. The present invention can be practiced in various modes different from the above-described embodiments as long as the polyphenylene ether derivative and the like of the present invention can be obtained.

Examples

[0101]

Hereinbelow, the present invention will be described in detail with reference to the following Examples, which should not be construed as limiting the scope of the present invention.

[0102]

[Production Example A-1: Production of polyphenylene ether derivative (A-1)]

Toluene, polyphenylene ether having a number average molecular weight of about 16,000, and p-aminophenol were charged into a glass flask container having a capacity of 2 liters and being equipped with a thermometer, a reflux condenser, and a stirrer and being capable of heating and cooling the contents of the flask, and dissolved with stirring at 90°C.

After confirming the dissolution visually, t-butylperoxyisopropyl monocarbonate and manganese naphthenate were added to the resultant solution to perform a reaction at a solution temperature of 90°C for 4 hours, and then cooled to 70°C to give a polyphenylene ether compound (A') having a primary amino group at the end of the molecule. A small portion of the resultant reaction solution was taken and subjected to GPC (polystyrene-equivalent measurement, eluent: tetrahydrofuran). As a result, it was found that the peak derived from p-aminophenol disappeared and the polyphenylene ether compound had a number average molecular weight of about 9,200. Further, another small portion of the reaction solution was taken and dropwise added to a methanol/benzene mixed solvent (mass ratio in the mixed solvent: 1:1) to cause reprecipitation, and the resultant purified solid material was subjected to FT-IR measurement. The result of the FT-IR measurement confirmed that a peak derived from a primary amino group appeared at around 3,400 cm⁻¹.

[0103]

Here, the number average molecular weight was measured by gel permeation chromatography (GPC) in which standard polystyrenes were used for obtaining a molecular weight conversion calibration curve. The calibration curve was obtained using standard polystyrenes: TSK standard POLYSTYRENE (Type; A-2500, A-5000, F-1, F-2, F-4, F-10, F-20, F-40) [trade name, manufactured by Tosoh Corp.] and approximated to a cubic equation. Conditions for GPC are shown below.

Apparatus: (Pump: L-6200 Model [manufactured by Hitachi High Technologies Corporation]),

(Detector: L-3300 Model RI [manufactured by Hitachi High Technologies Corporation]),

(Column oven: L-655A-52 [manufactured by Hitachi High Technologies Corporation])

Column: Guard column: TSK Guard column HHR-L + Column: TSK

gel-G4000HHR + TSK gel-G2000HHR (trade name, each of which is manufactured by Tosoh Corp.)

Column size: 6.0 × 40 mm (guard column), 7.8 × 300 mm (column)

Eluent: Tetrahydrofuran

Concentration of a sample: 30 mg/5 mL

Amount of a sample per injection: 20 µL

Flow rate: 1.00 mL/minute

Temperature for measurement: 40°C

[0104]

Then, 3,3'-dimethyl-5,5'-diethyl-4,4'-diphenylmethanebismaleimide and propylene glycol monomethyl ether were added to the above-obtained reaction solution, and the temperature of the resultant mixture was increased while stirring, and, while maintaining the temperature at 120°C, a reaction was conducted for 4 hours, followed by cooling and 200-mesh filtration, to produce a polyphenylene ether derivative (A-1). A small portion of the resultant reaction solution was taken and subjected to reprecipitation in the same manner as mentioned above, and the resultant purified solid material was subjected to FT-IR measurement. The result of the FT-IR measurement confirmed that the peak at around 3,500 cm⁻¹ derived from a primary amino group disappeared and a peak of a carbonyl group appeared at 1,700 to 1,730 cm⁻¹. Further, the solid material was subjected to GPC measurement (under the same conditions as mentioned above). As a result, the number average molecular weight was found to be about 9,400.

The amount of each component used is shown in Table 1.

[0105]

[Production Example A-2: Production of polyphenylene ether derivative (A-2)]

A polyphenylene ether derivative (A-2) was produced in the same manner as in Production Example A-1 except that, instead of 3,3'-dimethyl-5,5'-diethyl-4,4'-diphenylmethanebismaleimide, 2,2-bis(4-(4-maleimidophenoxy)phenyl)propane was used, and the individual components with the formulation shown in Table 1 were used. The polyphenylene ether derivative (A-2) had a number average molecular weight of about 9,400.

The amount of each component used is shown in Table 1.

[0106]

[Production Example A-3: Production of polyphenylene ether derivative (A-3)]

A polyphenylene ether derivative (A-3) was produced in the same manner as in Production Example A-1 except that, instead of 3,3'-dimethyl-5,5'-diethyl-4,4'-diphenylmethanebismaleimide, 1,6-bismaleimido-(2,2,4-trimethyl)hexane was used, and the individual components with the formulation shown in Table 1 were used. The polyphenylene ether derivative (A-3) had a number average molecular weight of about 9,500.

The amount of each component used is shown in Table 1.

[0107]

[Production Example A-4: Production of polyphenylene ether derivative (A-4)]

A polyphenylene ether derivative (A-4) was produced in the same manner as in Production Example A-2 except that, instead of p-aminophenol, m-aminophenol was used. The polyphenylene ether derivative (A-4) had a number average molecular weight of about 9,400.

The amount of each component used is shown in Table 1.

[0108]

[Production Example A-5: Production of polyphenylene ether derivative (A-5)]

A polyphenylene ether derivative (A-5) was produced in the same manner as in Production Example A-2 except that p-aminophenol and 2,2-bis(4-(4-maleimidophenoxy)phenyl)propane were used and the individual components with the formulation shown in Table 1 were used. The polyphenylene ether derivative (A-5) had a number average molecular weight of about 5,000.

The amount of each component used is shown in Table 1.

[0109]

(Production Example A-6: Production of polyphenylene ether derivative (A-6))

A polyphenylene ether derivative (A-6) in Production Example A-6 was produced in the same manner as in Production Example A-2 except that p-aminophenol and 2,2-bis(4-(4-maleimidophenoxy)phenyl)propane were used and the individual components with the formulation shown in Table 1 were used. The polyphenylene ether derivative (A-6) had a number average molecular weight of about 12,000.

The amount of each component used is shown in Table 1.

[0110]

Table 1 - Production of Component (A)

		Production Example					
		A-1	A-2	A-3	A-4	A-5	A-6
Polyphenylene Ether	PPO640	100	100	100	100	100	100
Number Average Molecular Weight		about 16,000	about 16,000	about 16,000	about 16,000	about 16,000	about 16,000
Aminophenol Compound (XIII)	p-aminophenol	1.35	1.35	1.35		3.8	0.8
	m-aminophenol				1.35		
Bismaleimide Compound (XV)	BMI-5100	5.5					
	BMI-4000		7.2		7.2	20	4.3
	BMI-TMH			4			
Reaction Catalyst	Perbutyl I	2	2	2	2	2	2
	manganese naphthenate	0.15	0.15	0.15	0.15	0.15	0.15
Organic Solvent	toluene	190	190	190	190	200	200
	propylene glycol monomethyl ether	12	15	9	15	40	8
Number Average Molecular Weight of Polyphenylene Ether Derivative (A)		9,400	9,400	9,500	9,400	5,000	12,000

Unit of amount: part by mass

[0111]

Abbreviations of the materials in Table 1 are as follows.

(1) Polyphenylene ether

PPO640: polyphenylene ether (manufactured by SABIC Innovative Plastics Japan LLC.), number average molecular weight = about 16,000, trade name

(2) Aminophenol compound (VIII)

p-Aminophenol: manufactured by Ihara Chemical Industry Co., Ltd.

m-Aminophenol: manufactured by Kanto Chemical Co., Ltd.

(3) Bismaleimide compound (IX)

BMI-5100: 3,3'-dimethyl-5,5'-diethyl-4,4'-diphenylmethanebismaleimide, trade name (manufactured by Daiwa Kasei Industry Co., Ltd.)

BMI-4000: 2,2-bis(4-(4-maleimidophenoxy)phenyl)propane, trade name (manufactured by Daiwa Kasei Industry Co., Ltd.)

BMI-TMH: 1,6-bismaleimido-(2,2,4-trimethyl)hexane, trade name (manufactured by Daiwa Kasei Industry Co., Ltd.)

(4) Reaction catalyst

Perbutyl (registered trademark) I: t-butylperoxyisopropyl monocarbonate (manufactured by NOF Corporation)

Manganese naphthenate (manufactured by Wako Pure Chemical Industries, Ltd.)

(5) Organic solvent

Toluene (manufactured by Kanto Chemical Co., Ltd.)

Propylene glycol monomethyl ether (manufactured by Kanto Chemical Co., Ltd.)

[0112]

[Production Example B-1: Production of polyaminobismaleimide compound (B-1)]

2,2-Bis(4-(4-maleimidophenoxy)phenyl)propane, 2,2-bis(4-(4-aminophenoxy)phenyl)propane and propylene glycol monomethyl ether were charged into a glass flask container having a capacity of 1 liter and being equipped with a thermometer, a reflux condenser, and a stirrer and being capable of heating and cooling the contents of the flaks, and, while maintaining the temperature thereof at 120°C and stirring, the resultant mixture was reacted for 3 hours, and then cooled and filtered through a 200-mesh filter to produce a polyaminobismaleimide compound (B-1).

The amount of each component used is shown in Table 2.

[0113]

[Production Example B-2: Production of polyaminobismaleimide compound (B-2)]

A polyaminobismaleimide compound (B-2) was produced in the same manner as in Production Example B-1 except that, instead of 2,2-bis(4-(4-aminophenoxy)phenyl)propane, 4,4'-[1,4-phenylenebis(1-methylethylidene)]bisaniiline was used in the amounts shown in Table 2.

The amount of each component used is shown in Table 2.

[0114]

[Production Example B-3: Production of polyaminobismaleimide compound (B-3)]

A polyaminobismaleimide compound (B-3) was produced in the same manner as in Production Example B-1 except that, instead of 2,2-bis(4-(4-maleimidophenoxy)phenyl)propane and 2,2-bis(4-(4-aminophenoxy)phenyl)propane, 2,2-bis(4-(4-maleimidophenoxy)phenyl)propane, 3,3'-dimethyl-5,5'-diethyl-4,4'-diphenylmethanebismaleimide and 4,4'-[1,3-phenylenebis(1-methylethylidene)]bisaniiline were used in the amounts shown in Table 2.

The amount of each component used is shown in Table 2.

[0115]

[Production Example B-4: Production of phenol-modified cyanate prepolymer (B-4)]

Toluene, 2,2-bis(4-cyanatophenyl)propane, and p-(α -cumyl)phenol were charged into a glass flask container having a capacity of 1 liter and being equipped with a thermometer, a reflux condenser, and a stirrer and being capable of heating and cooling the contents of the flasks. After the dissolution of the solid material was confirmed visually, manganese naphthenate as a reaction catalyst was added to the solution with stirring at 110°C to perform a reaction for 3 hours, followed by cooling and 200-mesh filtration, to produce a phenol-modified cyanate prepolymer solution (B-4)

The amount of each component used is shown in Table 2.

[0116]

Table 2 - Production of Component (B)

		Production Example			
		B-1	B-2	B-3	B-4
Polymaleimide Compound(a)	BMI-5100			50	
	BMI-4000	100	100	50	
Aromatic Diamine Compound (b)	BAPP	15			
	Bisaniline-P		12		
	Bisaniline-M			14	
Cyanate Resin	BADCy				100
Monophenol Compound	p-(α -cumyl)phenol				1.55
Reaction Catalyst	manganese naphthenate				0.03
Organic Solvent	toluene				44
	propylene glycol monomethyl ether	50	48	50	

Unit of amount: part by mass

[0117]

Abbreviations of the materials in Table 2 are as follows.

(1) Polymaleimide compound (a)

BMI-5100: 3,3'-dimethyl-5,5'-diethyl-4,4'-diphenylmethanebismaleimide, trade name, (manufactured by Daiwa Kasei Industry Co., Ltd.)

BMI-4000: 2,2-bis(4-(4-maleimidophenoxy)phenyl)propane, trade name, (manufactured by Daiwa Kasei Industry Co., Ltd.)

(2) Aromatic diamine compound (b)

BAPP: 2,2-bis(4-(4-aminophenoxy)phenyl)propane, trade name (manufactured by Wakayama Seika Kogyo Co., Ltd.)

Bisaniline-P: 4,4'-[1,4-phenylenebis(1-methylethylidene)]bisaniline, trade name (manufactured by Mitsui Chemicals, Inc.)

Bisaniline-M: 4,4'-[1,3-phenylenebis(1-methylethylidene)]bisaniline, trade name (manufactured by Mitsui Chemicals, Inc.)

(3) Cyanate resin

BADCy: Primaset (registered trademark) BADCy, 2,2-bis(4-cyanatophenyl)propane (manufactured by Lonza Group AG)

(4) Monophenol compound

p-(α -cumyl)phenol (manufactured by Mitsui Fine Chemicals, Inc.)

(5) Reaction catalyst

Manganese naphthenate (manufactured by Wako Pure Chemical Industries, Ltd.)

[0118]

[Examples 1 to 28, Comparative Examples 1 to 20: Preparation of resin composition]

The components shown in Tables 3 to 7 were stirred and mixed according to the formulation of blending quantities (unit: part by mass) shown in Tables 3 to 7 at room temperature or with heating at 50 to 80°C to prepare resin compositions having a solid content (nonvolatile component) concentration of 40 to 60% by mass.

Here, the resin composition (excluding inorganic filler) generally has a density of 1.20 to 1.25 g/cm³, and the inorganic filler used has a density of 2.2 to 3.01 g/cm³. Therefore, when 80 parts by mass of the inorganic filler is incorporated, relative to 100 parts by mass of the resin composition (excluding inorganic filler), the amount of the inorganic filler incorporated is about 30 to 34% by volume.

[0119]

<Evaluation/Measurement Method>

The resin compositions obtained in Examples and Comparative Examples were analyzed and evaluated according to the methods mentioned below. The results are shown in Tables 3 to 7.

[0120]

(1. Evaluation of compatibility of resin composition)

With respect to the resin compositions obtained in the above Example and those dried at 160°C for 10 minutes to remove the organic solvent therefrom, the appearance thereof was visually examined, and the compatibility was evaluated (whether macroscopic phase separation or unevenness was present or not) in

accordance with the criteria shown below.

A: Macroscopic phase separation or unevenness is not present.

B: Macroscopic phase separation or unevenness is present.

[0121]

(2. Formation of prepreg and copper-clad laminate)

The resin composition obtained in each Example was applied to glass cloth having a thickness of 0.1 mm (E glass, manufactured by Nitto Boseki Co., Ltd.), and then dried by heating at 160°C for 7 minutes to prepare a prepreg having a resin content of about 54% by mass. 6 sheets of the prepared prepreg were stacked on one another, and low profile copper foils having a thickness of 18 μm (FV-WS, M-side Rz: 1.5 μm ; manufactured by The Furukawa Electric Co., Ltd.) were disposed respectively on the top and bottom of the resultant laminate so that the M-side of each copper foil was in contact with the laminate, and subjected to hot pressing under conditions such that the temperature was 230°C (200°C in Comparative Examples 5 and 6), the pressure was 3.9 MPa, and the time was 180 minutes to prepare a double-sided copper-clad laminate (thickness: 0.8 mm).

(2-1. Evaluation of appearance of prepreg)

The appearance of the above-obtained prepreg was examined. The appearance was visually examined, and the prepreg was evaluated according to the criteria shown below.

A: Nothing wrong on appearance.

C: The prepreg surface has some unevenness, streak, foaming, phase separation and the like, and lacks surface smoothness.

(2-2. Evaluation of properties of copper-clad laminate)

With respect to the above-obtained copper-clad laminate, the formability, the dielectric properties, the copper foil peel strength, the glass transition temperature, the thermal expansion coefficient, the soldering heat resistance, and the flame retardancy thereof were evaluated. The methods for evaluation of the properties of the copper-clad laminate are as described below.

[0122]

(2-2-1) Formability

The appearance of the laminate having etched copper foils on both sides was examined to evaluate the formability. The formability was visually evaluated, and the laminate was evaluated according to the following criteria.

A: Nothing wrong on appearance.

C: The laminate has some unevenness, streak, thinned area, voids or the like, and lacks surface smoothness.

(2-2-2) Dielectric properties

The copper-clad laminate was immersed in a copper etchant, 10 mass% solution of ammonium persulfate (manufactured by Mitsubishi Gas Chemical Corporation) to remove the copper foil, and a test piece of 2 mm × 85 mm was cut out of the resultant substrate for evaluation.

The test piece was tested according to JPCA-TM001 (Triplate-line resonator method) at 10 GHz band.

[0123]

(2-2-3) Copper foil peel strength

Copper foil peel strength was measured in accordance with JIS-C-6481 (1996) to thereby determine the adhesion to conductor.

(2-2-4) Soldering heat resistance

A soldering heat resistance was evaluated using a 50 mm square test specimen having etched copper foils on both sides as follows. 3 specimens in a dry state and 3 specimens, which had been treated in a pressure cooker test (PCT) apparatus (conditions: 121°C, 2.2 atm.) for a predetermined period of time (1, 3, or 5 hours), were immersed in molten solder at 288°C for 20 seconds, and then the appearance of each of the resultant specimens was visually examined. The figures shown in the tables mean, among the 3 specimens obtained after immersed in the solder, the number of the specimen or specimens in which a defect, such as the occurrence of blistering or measling, was not recognized in the laminate.

(2-2-5) Glass transition temperature (T_g) and thermal expansion coefficient

Five mm square test pieces that had been etched to remove the copper foil from both sides thereof were analyzed in accordance with IPC (The Institute for Interconnecting and Packaging Electronic Circuits) Standards using a thermomechanical analyzer (TMA) [manufactured by TA Instruments Japan Corporation, Q400 (Model Number)] to measure the glass transition temperature (T_g) and the thermal expansion coefficient (linear expansion coefficient, thickness direction, temperature range: 30 to 150°C) thereof.

(2-2-6) Flame retardancy

The copper-clad laminate was immersed in a copper etchant, 10 mass% solution of ammonium persulfate (manufactured by Mitsubishi Gas Chemical

Corporation) to remove the copper foil, and a test piece having a length of 127 mm and a width of 12.7 mm was cut out of the resultant substrate for evaluation. The test piece was tested according to the test method (V method) of UL94 to evaluate the flame retardancy thereof.

Namely, the lower edge of the test piece held vertically was exposed to 20-mm flame for 10 seconds, twice in every test. The evaluation was carried out according to the criteria in the V method of UL94.

[0124]
Table 3

		Example											
		1	2	3	4	5	6	7	8	9	10	11	12
Polyphenylene Ether Derivative (A)	Polyphenylene Ether Derivative (A-1)	100	100	100	100	100	100	100	100				
	Polyphenylene Ether Derivative (A-2)												
	Polyphenylene Ether Derivative (A-3)								100				
	Polyphenylene Ether Derivative (A-4)									100			
	Polyphenylene Ether Derivative (A-5)										100		
	Polyphenylene Ether Derivative (A-6)											100	
Thermosetting Resin (B)	BM-4000 (bismaleimide)	88											
	NC-3000H (epoxy resin)		35										
	NC-7000L (epoxy resin)			26									
	Polyaminobismaleimide Compound (B-1)				126				126			126	126
	Polyaminobismaleimide Compound (B-2)					126							
	Polyaminobismaleimide Compound (B-3)						126						
Synthetic Thermoplastic Elastomer (C)	Phenol-Modified Cyanate Prepolymer (B-4)							100					
	Tuftec H1043	53	47	56	53	53	53	70	53	53	53	53	53
	SC-2050 WNK	237	161	158	238	238	238	234	237	237	237	237	237
	Pertuflyl-P	1.8			1.8	1.8	1.8		1.8	1.8	1.8	1.8	1.8
	G-8009L	0.9	0.7	0.26	0.9	0.9	0.9	0.3	0.9	0.9	0.9	0.9	0.9
	Manganese Naphthenate							0.015					
Flame Retardant (F)	OP-935	12	10	10	12	12	12	12	12	12	12	12	12
	HCA-HQ	8	7	7	8	8	8	7	8	8	8	8	8
	Toluene	106			69	69	69	72	69	69	69	69	69
	Methyl ethyl ketone		51	51									
Resin Composition	Compatibility	A	A	A	A	A	A	A	A	A	A	A	A
	Appearance	A	A	A	A	A	A	A	A	A	A	A	A
	Formability	A	A	A	A	A	A	A	A	A	A	A	A
	Dielectric Constant	3.6	3.8	3.7	3.5	3.6	3.6	3.7	3.8	3.6	3.7	3.8	3.6
	Dielectric Dissipation Factor	0.0047	0.0056	0.0055	0.0046	0.0048	0.0047	0.0050	0.0051	0.0046	0.0048	0.0046	0.0048
	Copper Foil Peel Strength (N/m)	0.62	0.69	0.68	0.66	0.60	0.64	0.61	0.65	0.69	0.64	0.68	0.69
Laminate	ordinary state	3	3	3	3	3	3	3	3	3	3	3	3
	after PCT-1 hr treatment	3	3	3	3	3	3	3	3	3	3	3	3
	after PCT-3 hr treatment	3	3	3	3	3	3	3	3	3	3	3	3
	after PCT-5 hr treatment	3	3	3	3	3	3	3	3	3	3	3	3
	Glass Transition Temperature (°C)	212	221	223	209	212	215	216	215	218	208	218	211
	Thermal Expansion Coefficient (ppm/°C)	38	36	38	41	44	38	41	43	44	41	42	41
		V-0	V-0	V-1	V-0	V-0	V-0	V-1	V-0	V-0	V-0	V-0	V-0

(The unit of content is part by mass. For solution, the content is in terms of solid content.)

[0125]

Table 4

				Example											
Polyphenylene Ether Derivative (A)	Polyphenylene Ether Derivative (A-1)	Thermosetting Resin (B)	Polyphenylene Ether Derivative (A-1) Polymindisimaleimide Compound (B-1)	solid concentration 35% by mass solid concentration 70% by mass	13	14	15	16	17	18	19	20	21	22	
					100	100	100	100	100	100	100	100	100	100	100
Styrenic Thermoplastic Elastomer (C)			Tuflec H1043		100	125	138	110	120	100	86	89	58	58	
			Tuflec H1051		245	53	44								
			Tuflec H1053					28							
			Tuflec H1052						21	12	5	3			
			Tuflec H1221												
Inorganic Filler (D)			Tuflec M1911												
			Tuflec M1943												
			SC-2050 KKK	solid concentration 70% by mass	522	251	251	200	200	167	144	144	174	41	
			Perbutyl-P		1.4	1.8	1.9	1.5	1.7	1.4	1.2	1.2	0.8	0.8	
			G-9009L	solid concentration 50% by mass	0.7	0.9	1.0	0.8	0.8	0.7	0.6	0.6	0.4	0.4	
Flame Retardant (F)			OP-935		35	12	12	10	10	8	7	7	8	8	
			HCA-HQ		25	8	8	6	6	5	5	5	12	12	
			Toluene		266	71	67	40	37	20	9	8	38	38	
			Methyl ethyl ketone												
			Compatibility	with solvent after solvent evaporation	A	A	A	A	A	A	A	A	A	A	A
Resin Composition			Appearance		A	A	A	A	A	A	A	A	A	A	
			Formability		A	A	A	A	A	A	A	A	A	A	
			Dielectric Constant		3.3	3.7	3.5	3.7	3.6	3.6	3.7	3.8	3.6	3.7	
			Dielectric Dissipation Factor		0.0042	0.0045	0.0046	0.0048	0.0048	0.0049	0.0050	0.0053	0.0048	0.0049	
			Copper Foil Peel Strength (kN/m)		0.61	0.68	0.65	0.68	0.67	0.69	0.70	0.72	0.68	0.66	
Laminate			ordinary state		3	3	3	3	3	3	3	3	3	3	
			after PCT-1 hr treatment		3	3	3	3	3	3	3	3	3	3	
			after PCT-3 hr treatment		3	3	3	3	3	3	3	3	3	3	
			after PCT-5 hr treatment		3	3	3	3	3	3	3	3	3	3	
			Glass Transition Temperature (°C)		216	211	216	220	219	225	227	231	208	209	
			Thermal Expansion Coefficient (ppm/°C)		46	39	38	41	43	36	32	30	41	39	
			Flame Retardancy		V-1	V-0	V-0	V-0	V-0	V-0	V-0	V-0	V-0	V-0	

The unit of content is part by mass. For solution, the content is in terms of solid content.)

(The unit of content is part by mass. For solution, the content is in terms of solid content.)

[0126]
Table 5

			Example						
Polyphenylene Ether Derivative (A)	Thermosetting Resin (B)	Polyphenylene Ether Derivative (A-1)	solid concentration 35% by mass	23	24	25	26	27	28
				100	100	100	100	100	100
Styrenic Thermoplastic Elastomer (C)	Thermosetting Resin (B)	Polyaminobismaleimide Compound (B-1)	solid concentration 70% by mass	58	125	57	50	50	100
		Tuftec P2000		41					
		Tuftec S2002			53				
		Tuftec S2005				25			
Inorganic Filler (D)	Thermosetting Resin (B)	SMA Resin EF-30					70		
		SMA Resin EF-80							
		SC-2050 KNK	solid concentration 70% by mass	165	251	142	209	175	245
Curing Accelerator (E)	Thermosetting Resin (B)	Perbutyl-P		0.8	1.8	0.8	0.7	0.7	1.4
		G-8009L	solid concentration 50% by mass	0.4	0.9	0.4	0.4	0.4	0.7
Flame Retardant (F)	Thermosetting Resin (B)	OP-935		8	12	7	14	12	35
		HCA-HQ		5	8	4	10	8	25
Organic Solvent	Thermosetting Resin (B)	Toluene		32	71	16	65	41	266
		Methyl ethyl ketone							
Resin Composition	Thermosetting Resin (B)	Compatibility	with solvent	A	A	A	A	A	A
		Appearance	after solvent evaporation	A	A	A	A	A	A
Prepreg	Thermosetting Resin (B)	Formability		A	A	A	A	A	A
		Dielectric Constant	10 GHz	3.6	3.6	3.7	3.6	3.7	3.6
Laminate	Thermosetting Resin (B)	Dielectric Dissipation Factor	10 GHz	0.0048	0.0047	0.0048	0.0047	0.0048	0.0047
		Copper Foil Peel Strength (kN/m)		0.69	0.67	0.65	0.69	0.64	0.67
	Thermosetting Resin (B)	Soldering Heat Resistance	ordinary state		3	3	3	3	3
			after PCT-1 hr treatment		3	3	3	3	3
			after PCT-3 hr treatment		3	3	3	3	3
			after PCT-5 hr treatment		3	3	3	3	3
	Thermosetting Resin (B)	Glass Transition Temperature (°C)		212	209	218	203	208	201
			Thermal Expansion Coefficient (ppm/°C)		38	41	37	38	41
	Flame Retardancy	Thermosetting Resin (B)		V-0	V-0	V-0	V-0	V-0	V-1

(The unit of content is part by mass. For solution, the content is in terms of solid content.)

[illegible]

(The unit of content is part by mass. For solution, the content is in terms of solid content.)

[0128]
Table 7

		Comparative Example									
		13	14	15	16	17	18	19	20		
Polyphenylene Ether Derivative (A)	Polyphenylene Ether Derivative (A-1)	100	100	100	100	100	100	100	100		
Thermosetting Resin (B)	Polyaminobismaleimide Compound (B-1)	122	50	125	100	50	50	125	100		
Non-styrenic Thermoplastic Elastomer	TOPAS 8007 TOPAS 6017	51	47	53	245						
Inorganic Filler (D)	SC-2050 KNK	98	62	100	179	100	62	100	179		
Curing Accelerator (E)	Perbutyl-P G-8009L	1.7	0.3	0.2	0.7	0.7	0.7	0.5	0.7		
Flame Retardant (F)	OP-935 HCA-HQ	0.9	0.2	0.1	0.4	0.4	0.4	0.2	0.4		
Organic Solvent	Toluene Methyl ethyl ketone	14 10 46	9 6 18	14 10 47	26 18 197	14 10 85	9 6 66	14 10 100	26 18 442		
Resin Composition	Compatibility	A	C	C	C	C	C	C	C		
Prepreg	Appearance	C	C	C	C	C	C	C	C		
	Formability	C	C	C	C	C	C	C	C		
	Dielectric Constant	3.6	3.8	3.9	3.8	3.7	3.8	3.7	3.8		
	Dielectric Dissipation Factor	0.0050	0.0049	0.0052	0.0048	0.0051	0.0052	0.0051	0.0048		
	Copper Foil Peel Strength (kN/m)	0.49	0.41	0.43	0.42	0.48	0.47	0.49	0.47		
	ordinary state	3	3	3	3	3	3	3	3		
	after PCT-1 hr treatment	3	3	3	3	3	3	3	3		
	after PCT-3 hr treatment	3	3	3	3	3	3	3	3		
	after PCT-5 hr treatment	3	3	3	3	3	3	3	3		
Laminate	Soldering Heat Resistance	211	209	210	192	211	204	208	193		
	Glass Transition Temperature (°C)	44	44	48	51	38	47	47	53		
	Thermal Expansion Coefficient (ppm/°C)	V-0	V-1	V-0	V-1	V-0	V-0	V-0	V-0		
	Flame Retardancy	V-0	V-1	V-0	V-1	V-0	V-0	V-0	V-0		

(The unit of content is part by mass. For solution, the content is in terms of solid content.)

[0129]

Abbreviations of the materials in Tables 3 to 7 are as follows.

(1) Thermosetting resin (B)

BMI-4000: 2,2-bis(4-(4-maleimidophenoxy)phenyl)propane (trade name, manufactured by Daiwa Kasei Industry Co., Ltd.)

NC-3000H: biphenylaralkyl-type epoxy resin (trade name, manufactured by Nippon Kayaku Co., Ltd.)

NC-7000L: naphthol novolak-type epoxy resin (trade name, manufactured by Nippon Kayaku Co., Ltd.)

(2) Styrenic thermoplastic elastomer (C)

Tuftec (registered trademark) H1043: SEBS, styrene content = 67% by mass (manufactured by Asahi Kasei Chemicals Corporation)

Tuftec (registered trademark) H1051: SEBS, styrene content = 42% by mass (manufactured by Asahi Kasei Chemicals Corporation)

Tuftec (registered trademark) H1053: SEBS, styrene content = 29% by mass (manufactured by Asahi Kasei Chemicals Corporation)

Tuftec (registered trademark) H1052: SEBS, styrene content = 20% by mass (manufactured by Asahi Kasei Chemicals Corporation)

Tuftec (registered trademark) H1221: SEBS, styrene content = 12% by mass (manufactured by Asahi Kasei Chemicals Corporation)

Tuftec (registered trademark) M1911: SEBS, styrene content = 30% by mass (manufactured by Asahi Kasei Chemicals Corporation)

Tuftec (registered trademark) M1913: SEBS, styrene content = 20% by mass (manufactured by Asahi Kasei Chemicals Corporation)

Tuftec (registered trademark) P2000: SBBS, styrene content = 67% by mass (manufactured by Asahi Kasei Chemicals Corporation)

Septon (registered trademark) 2002: SEPS, styrene content = 30% by mass (manufactured by Kuraray Co., Ltd.)

Septon (registered trademark) 2005: SEPS, styrene content = 20% by mass (manufactured by Kuraray Co., Ltd.)

SMA (registered trademark) Resin EF-30 (manufactured by Cray Valley Technologies USA) (styrene content = 75% by mass)

SMA (registered trademark) Resin EF-80 (manufactured by Cray Valley Technologies USA) (styrene content = 89% by mass)

(3) Non-styrenic thermoplastic elastomer

TOPAS (registered trademark) 8007: cycloolefin copolymer (norbornene-derived structural unit content = 64%) (manufactured by Topas Advanced Polymers)

TOPAS (registered trademark) 6017: cycloolefin copolymer (norbornene-derived structural unit content = 82%) (manufactured by Topas Advanced Polymers)

(4) Inorganic filler (D)

SC-2050 KNK: spherical molten silica, mean particle size = 0.5 μm , surface treatment: vinylsilane coupling agent (1% by mass/solid content), dispersant: methyl isobutyl ketone, solid concentration 70% by mass, density 2.2 g/cm^3 (trade name, manufactured by Admatechs Company Limited)

(5) Curing accelerator (E)

Perbutyl (registered trademark) P: α,α' -bis(t-butylperoxy)diisopropylbenzene (trade name, manufactured by NOF Corp.)

G-8009L: isocyanate-masked imidazole (addition product of hexamethylene-diisocyanate resin and 2-ethyl-4-methylimidazole) (trade name, manufactured by Dai-ichi Kogyo Seiyaku Co., Ltd.)

Manganese naphthenate (manufactured by Wako Pure Chemical Industries, Ltd.)

(6) Flame retardant (F)

OP-935: aluminum dialkylphosphinate, metal salt of disubstituted phosphinic acid, phosphorus content: 23.5% by mass (trade name, manufactured by Clariant Corp.)

HCA-HQ:
10-(2,5-dihydroxyphenyl)-9,10-dihydro-9-oxa-10-phosphaphenanthrene-10-oxide, cyclic organic phosphorus compound, phosphorus content: 9.6% by mass (manufactured by Sanko Co., Ltd.)

[0130]

As obvious from the results shown in Tables 3 to 5, Examples of the present invention are excellent in compatibility of the resin compositions and appearance of the prepregs, and the copper-clad laminates produced using these are good and well-balanced in all the formability, the high frequency properties (dielectric properties), the adhesion to conductor, the soldering heat resistance, the glass transition temperature, the thermal expansion coefficient and the flame

retardancy.

On the other hand, as obvious from the results in Tables 6 and 7, in Comparative Examples, some resin compositions and prepregs are not good in compatibility and appearance (Comparative Examples 13 to 20). In addition, the copper-clad laminates of Comparative Examples are inferior to those of Examples in point of any of formability, dielectric properties, adhesion to conductor, soldering heat resistance, glass transition temperature, thermal expansion coefficient and flame retardancy.

Industrial Applicability

[0131]

Using a specific thermosetting resin composition along with a polyphenylene ether derivative having a specific structure and a styrenic thermoplastic elastomer, a resin composition having good compatibility, especially excellent high frequency properties (low dielectric constant, low dielectric dissipation factor), high adhesion to conductor, excellent heat resistance, high glass transition temperature, low thermal expansion coefficient and high flame retardancy can be obtained.

In addition, for the resin composition of the present invention, the material cost and the production cost for substrate material can be suppressed, and the working environment is excellent, and therefore, the prepreg and the laminate to be provided using the resin composition can be favorably used for use for electronic parts such as multilayer printed wiring boards, etc.

CLAIMS

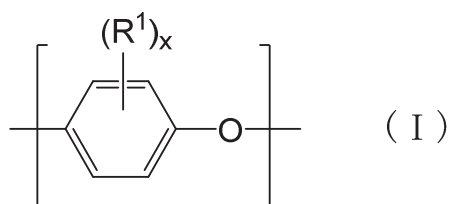
[Claim 1]

A resin composition comprising:

(A) a polyphenylene ether derivative having an N-substituted maleimide structure-containing group and a structural unit represented by the following general formula (I) in one molecule,

(B) at least one thermosetting resin selected from the group consisting of an epoxy resin, a cyanate resin and a maleimide compound, and

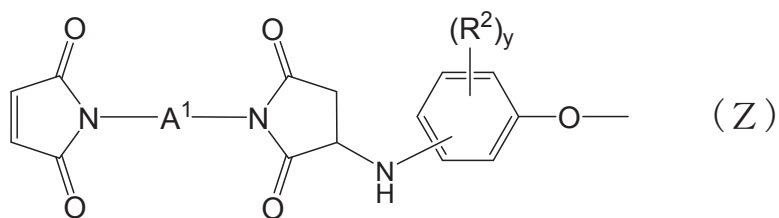
(C) a styrenic thermoplastic elastomer:



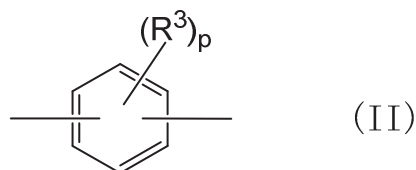
wherein R¹ each independently represents an aliphatic hydrocarbon group having 1 to 5 carbon atoms, or a halogen atom, and x represents an integer of 0 to 4.

[Claim 2]

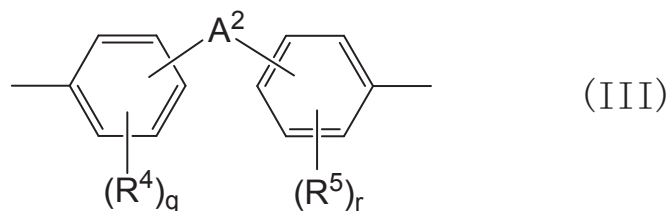
The resin composition according to claim 1, wherein the N-substituted maleimide structure-containing group is a group represented by the following general formula (Z):



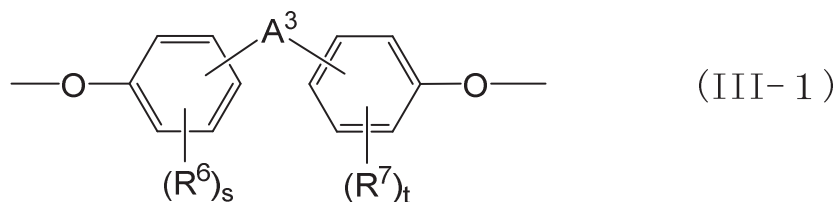
wherein R² each independently represents an aliphatic hydrocarbon group having 1 to 5 carbon atoms, or a halogen atom, y represents an integer of 0 to 4, and A¹ represents a group represented by the following general formula (II), (III), (IV) or (V):



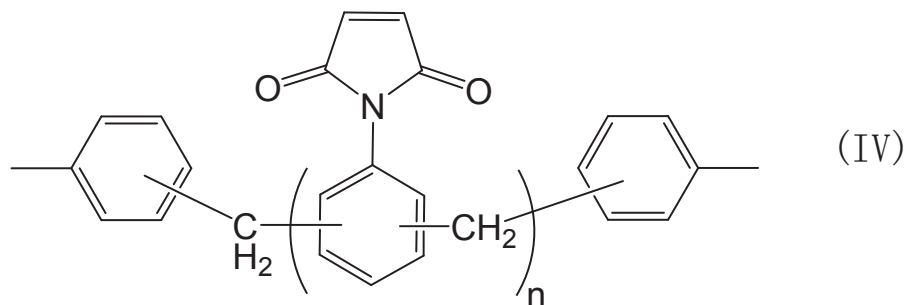
wherein R^3 each independently represents an aliphatic hydrocarbon group having 1 to 5 carbon atoms, or a halogen atom, and p represents an integer of 0 to 4:



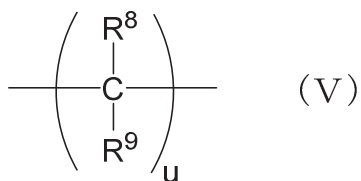
wherein R^4 and R^5 each independently represent an aliphatic hydrocarbon group having 1 to 5 carbon atoms, or a halogen atom, A^2 represents an alkylene group having 1 to 5 carbon atoms, an alkylidene group having 2 to 5 carbon atoms, an ether group, a sulfide group, a sulfonyl group, a carbonyloxy group, a keto group, a single bond, or a group represented by the following general formula (III-1), and q and r each independently represent an integer of 0 to 4:



wherein R^6 and R^7 each independently represent an aliphatic hydrocarbon group having 1 to 5 carbon atoms, or a halogen atom, A^3 represents an alkylene group having 1 to 5 carbon atoms, an isopropylidene group, an ether group, a sulfide group, a sulfonyl group, a carbonyloxy group, a keto group or a single bond, and s and t each independently represent an integer of 0 to 4:



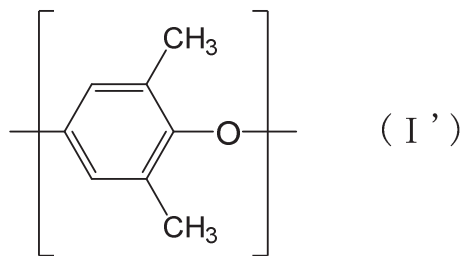
wherein n represents an integer of 0 to 10,



wherein R⁸ and R⁹ each independently represent a hydrogen atom, or an aliphatic hydrocarbon group having 1 to 5 carbon atoms, and u represents an integer of 1 to 8.

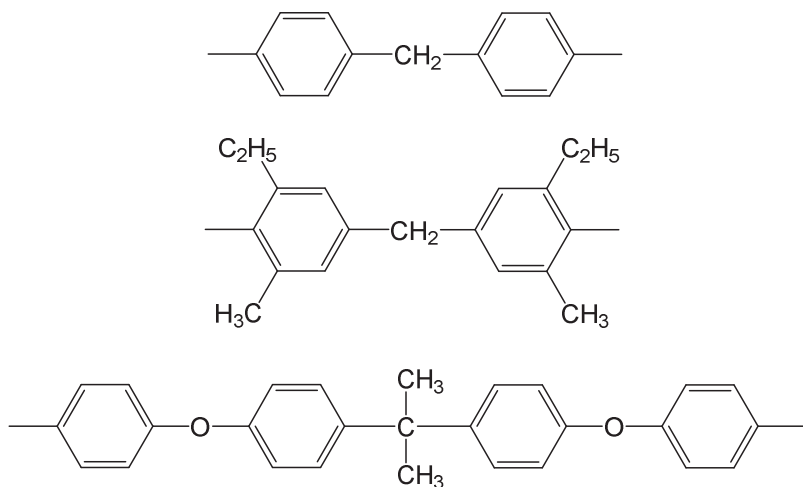
[Claim 3]

The resin composition according to claim 1 or 2, wherein the structural unit represented by the general formula (I) is a structural unit represented by the following formula (I'):



[Claim 4]

The resin composition according to any one of claims 1 to 3, wherein A¹ in the general formula (Z) is a group represented by any of the following formulae:



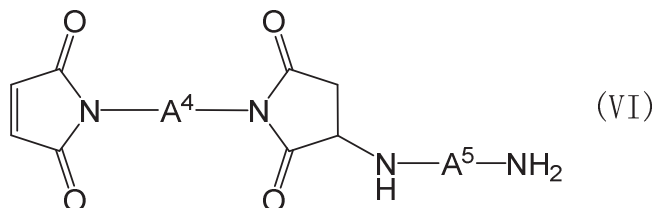
[Claim 5]

The resin composition according to any one of claims 1 to 4, wherein the number average molecular weight of the component (A) is from 5,000 to 12,000.

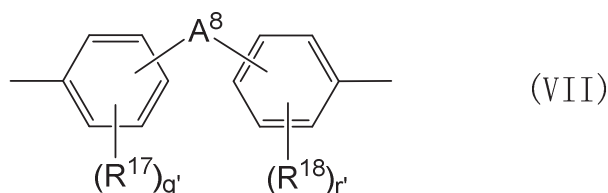
[Claim 6]

The resin composition according to any one of claims 1 to 5, wherein the

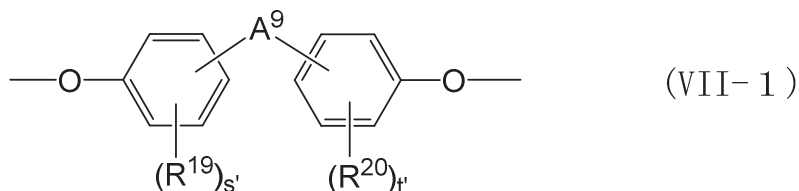
maleimide compound in the component (B) is a polymaleimide compound (a) having at least two N-substituted maleimide groups in one molecule, or a polyaminobismaleimide compound (c) represented by the following general formula (VI):



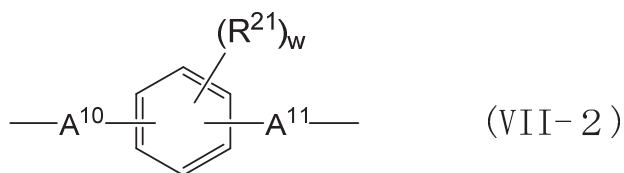
wherein A^4 has the same definition as that of A^1 in the general formula (Z), and A^5 represents a group represented by the following general formula (VII):



wherein R^{17} and R^{18} each independently represent an aliphatic hydrocarbon group having 1 to 5 carbon atoms, an alkoxy group having 1 to 5 carbon atoms, a hydroxyl group or a halogen atom, A^8 represents an alkylene group having 1 to 5 carbon atoms, an alkylidene group having 2 to 5 carbon atoms, an ether group, a sulfide group, a sulfonyl group, a carbonyloxy group, a keto group, a fluorenylene group, a single bond, or a group represented by the following general formula (VII-1) or (VII-2), and q' and r' each independently represent an integer of 0 to 4:



wherein R^{19} and R^{20} each independently represent an aliphatic hydrocarbon group having 1 to 5 carbon atoms, or a halogen atom, A^9 represents an alkylene group having 1 to 5 carbon atoms, an isopropylidene group, an m-phenylenediisopropylidene group, a p-phenylenediisopropylidene group, an ether group, a sulfide group, a sulfonyl group, a carbonyloxy group, a keto group or a single bond, and s' and t' each independently represent an integer of 0 to 4:



wherein R^{21} represents an aliphatic hydrocarbon group having 1 to 5 carbon atoms, or a halogen atom, A^{10} and A^{11} each independently represent an alkylene group having 1 to 5 carbon atoms, an isopropylidene group, an ether group, a sulfide group, a sulfonyl group, a carbonyloxy group, a keto group, or a single bond, and w represents an integer of 0 to 4.

[Claim 7]

The resin composition according to any one of claims 1 to 6, wherein the content ratio of the component (A) to the component (B) $[(A)/(B)]$ is from 5/95 to 80/20 by mass.

[Claim 8]

The resin composition according to any one of claims 1 to 7, wherein the component (C) is at least one selected from a styrene-butadiene-styrene block copolymer hydrogenate (SEBS, SBBS), a styrene-isoprene-styrene block copolymer hydrogenate (SEPS) and a styrene-maleic anhydride copolymer (SMA).

[Claim 9]

The resin composition according to any one of claims 1 to 8, wherein the content ratio of the component (C) is from 5 to 60 parts by mass relative to 100 parts by mass of the sum total of the components (A) to (C).

[Claim 10]

The resin composition according to any one of claims 1 to 9, further comprising an inorganic filler (D).

[Claim 11]

The resin composition according to any one of claims 1 to 10, further comprising a curing accelerator (E).

[Claim 12]

The resin composition according to any one of claims 1 to 11, further comprising a flame retardant (F).

[Claim 13]

The resin composition according to any one of claims 1 to 12, further comprising an organic solvent.

[Claim 14]

A prepreg comprising the resin composition of any one of claims 1 to 13 and a sheet-form fiber reinforced substrate.

[Claim 15]

A laminate comprising the prepreg of claim 14 and a metal foil.

[Claim 16]

A multilayer printed wiring board comprising the prepreg of claim 14 or the laminate of claim 15.